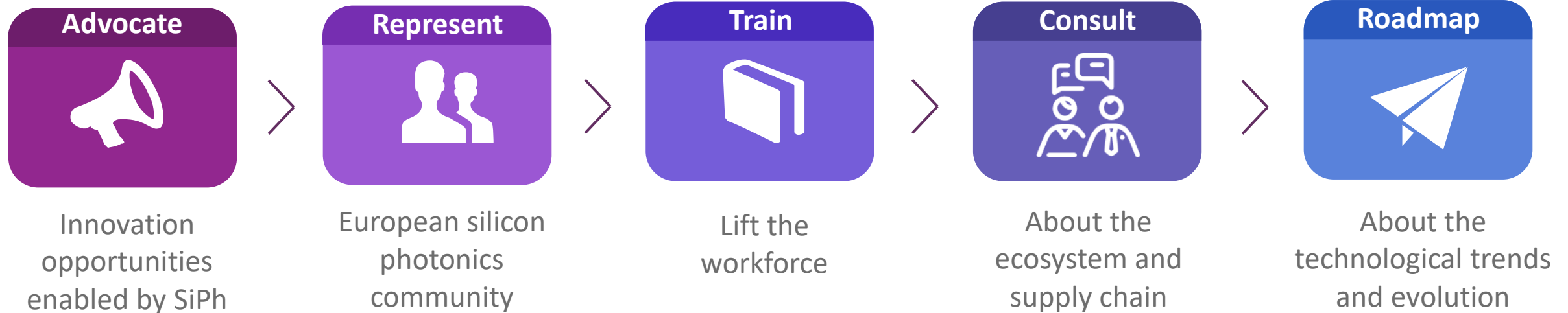


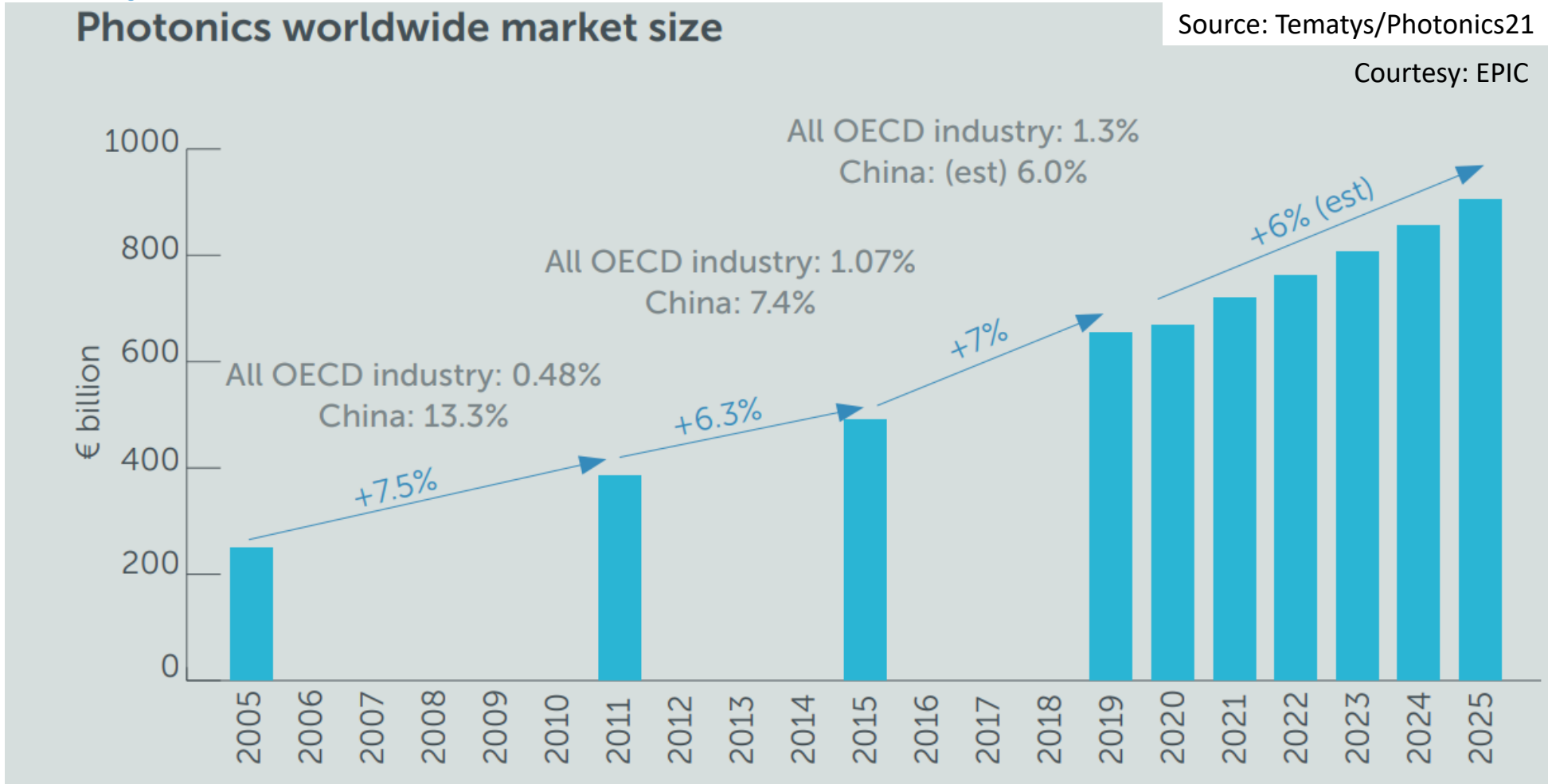
# **Silicon Photonics: (a, b) current state, future evolution, and (c) trends**

**Dr. Abdul Rahim (Program Manager)  
ePIXfab – the European Silicon Photonics Alliance  
Ghent University, Belgium**

# ePIXfab - The European Silicon Photonics Alliance

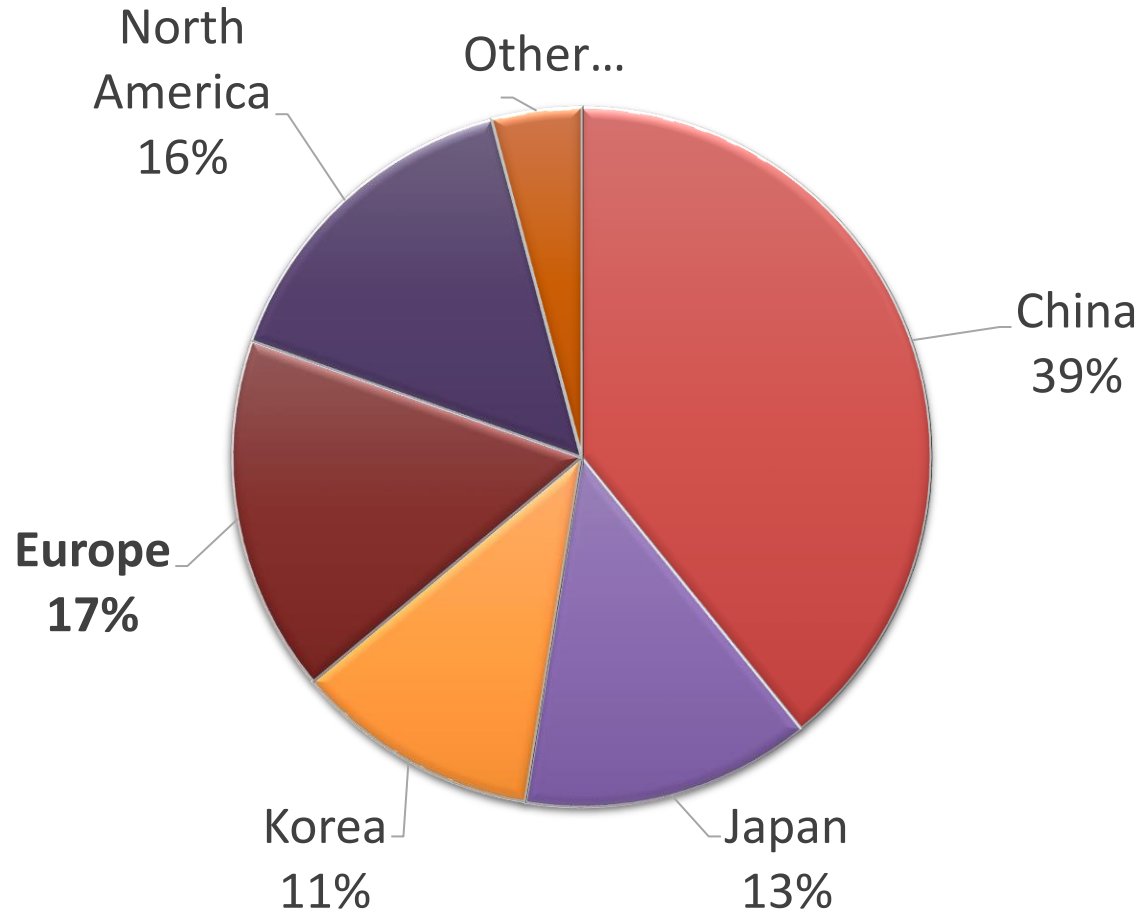
**ePIXfab's mission is to act as a catalyst for European academia and industry to strengthen the worldwide silicon photonics ecosystem.**





**Global Photonics market expected to reach €900 billion in 2025**

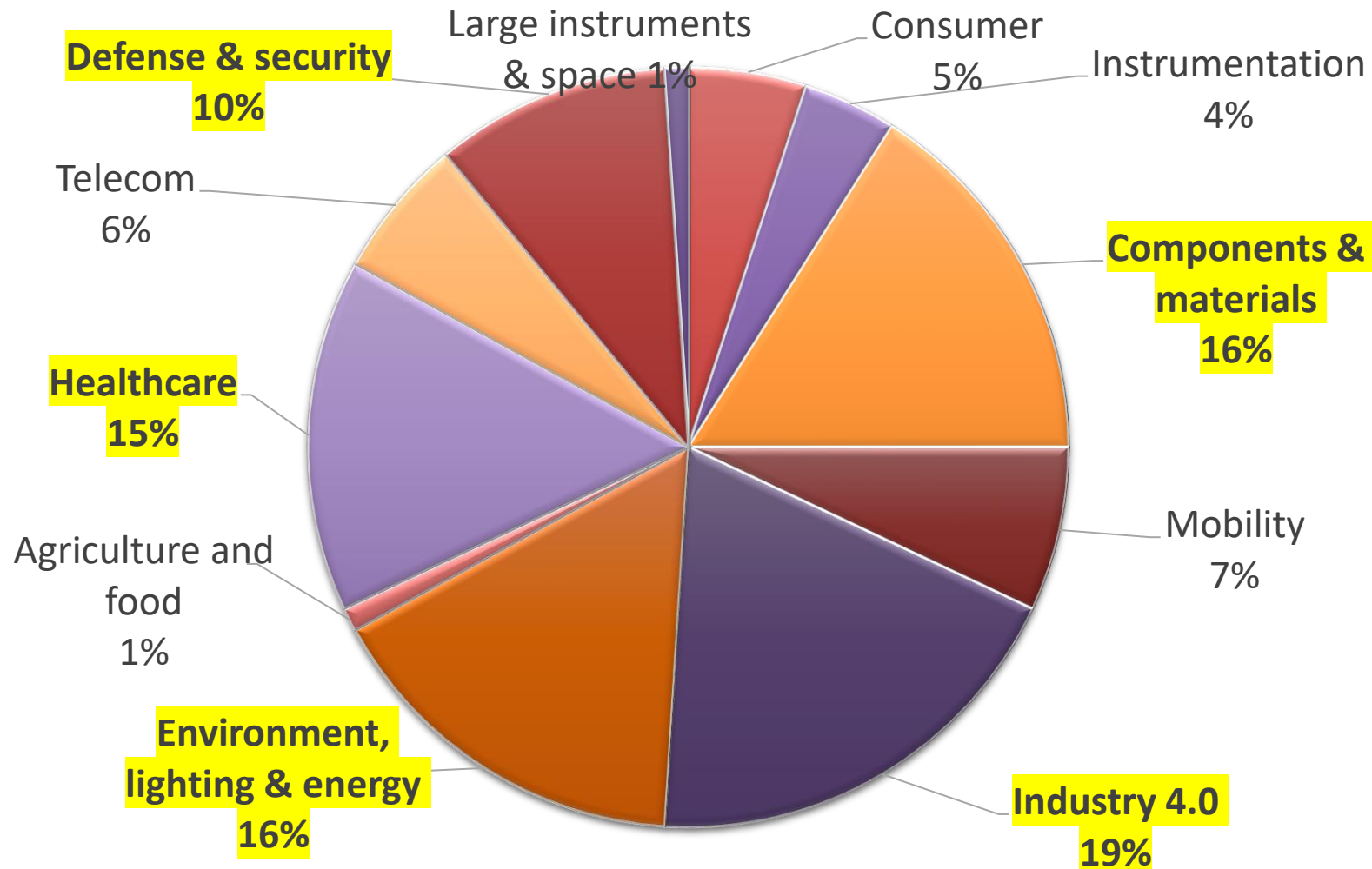
Source: Tematys/Photonics21  
Courtesy: EPIC



## Global photonics market share:

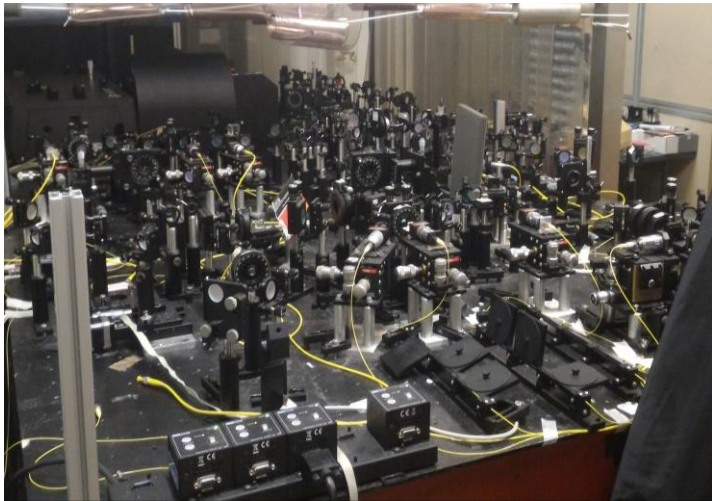
- From 2015 to 2019, the share of the **European photonics industry has been maintained at 17%** of the global market thanks to the creativity of the European Research and the dynamism of companies active in “mid-size” markets.
- Asia photonics industry is mainly focus in displays, PV, and LED production

Source: Tematys/Photonics21  
Courtesy: EPIC





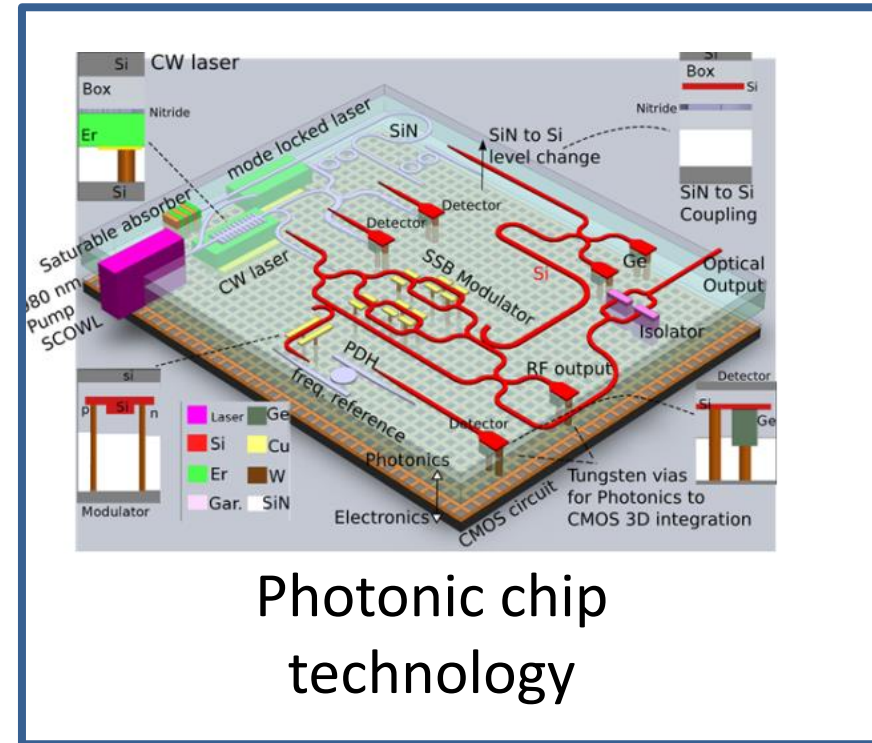
# Different forms of photonics



Free space optical  
technology

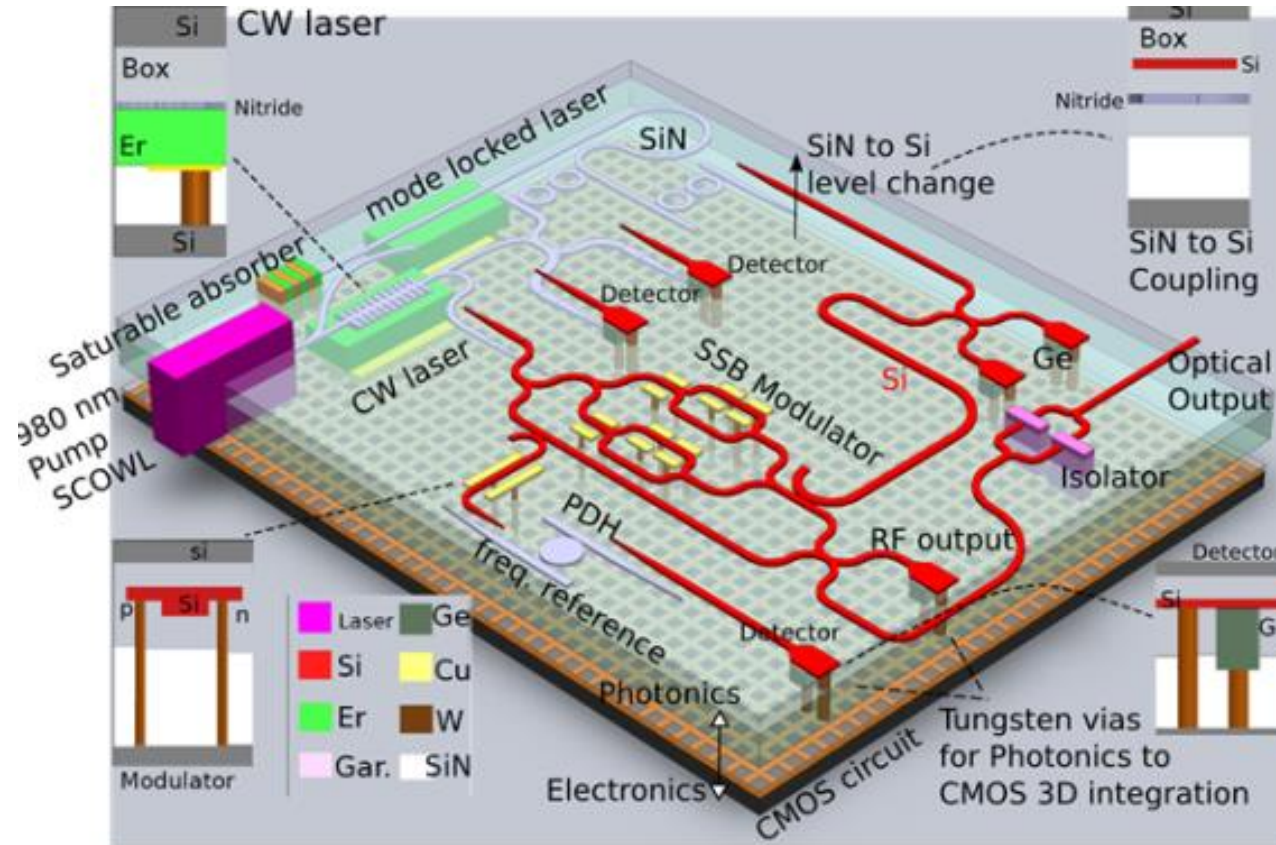


Optical fiber  
technology



Photonic chip  
technology

# Photonics Integrated Circuits (PICs)



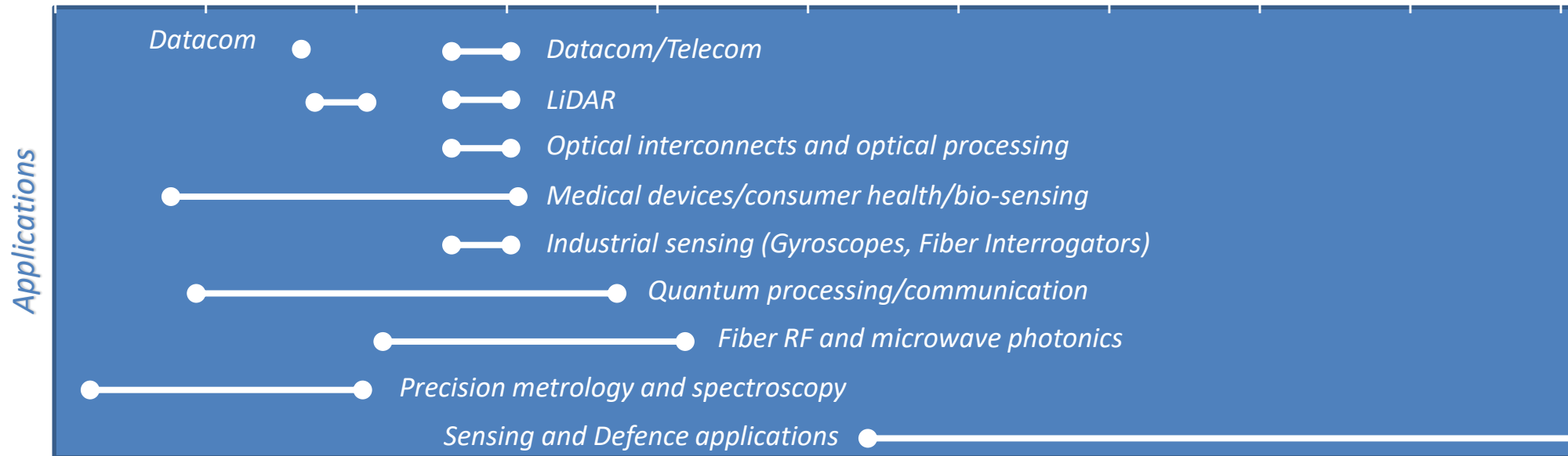
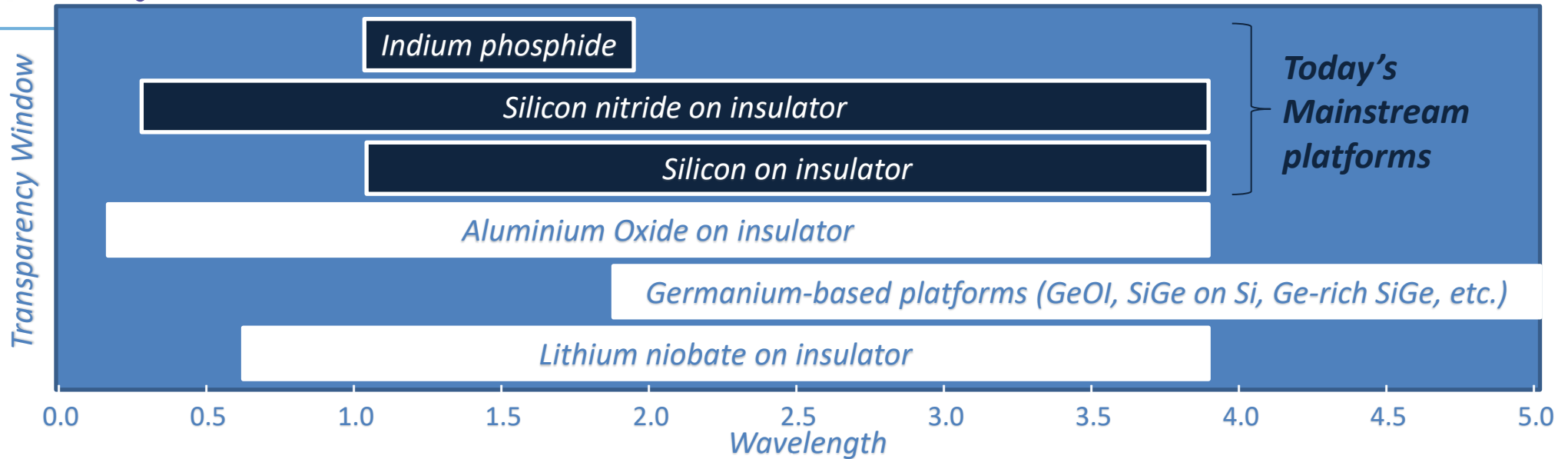
Source: EECS Berkeley



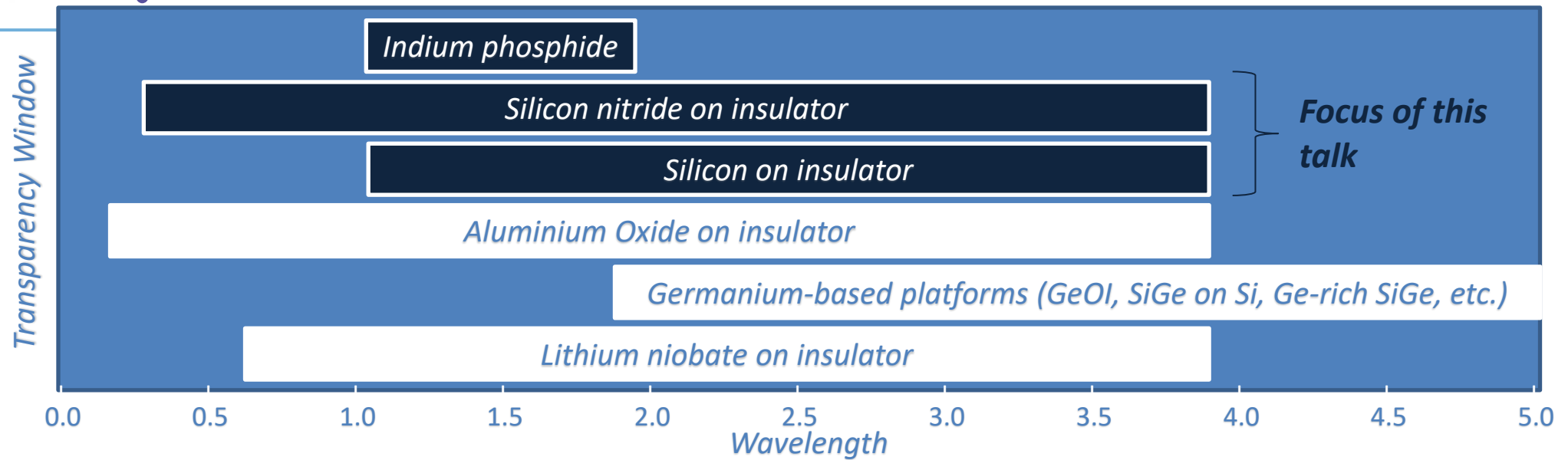
**PICs provide a route to commoditize photonics at larger volumes and lower costs**

# PICs: platforms & application landscape

*Not exhaustive*





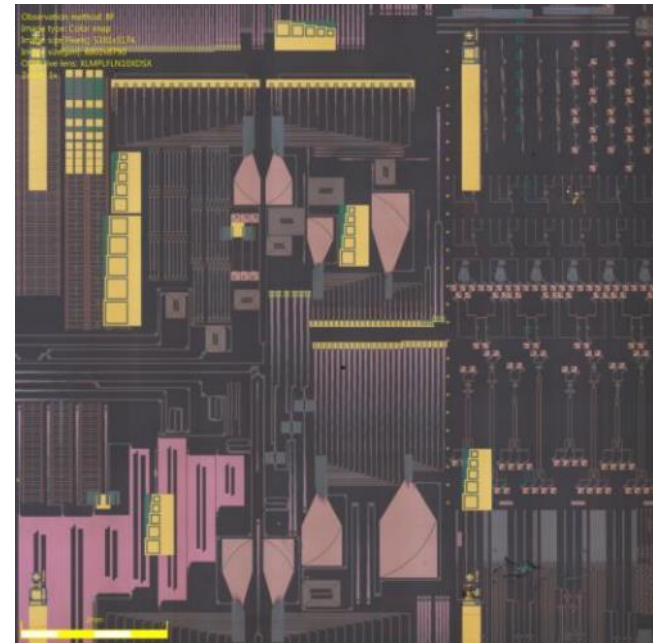


## What else is not covered in this talk:

- X PICs based on Compound semiconductors, R&D platforms, emerging platforms
- X Imager chips
- X VCSEL Arrays

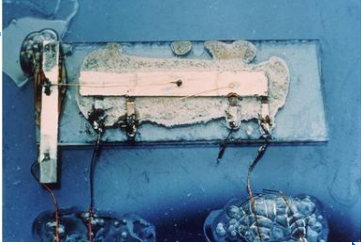
# What is silicon photonics?

The implementation of high density photonic integrated circuits by means of CMOS process technology in a CMOS fab



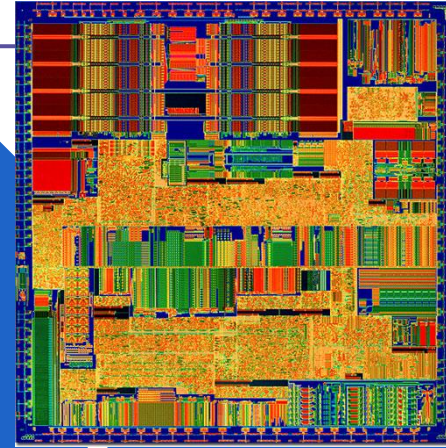
Enabling complex optical functionality on a compact chip at low cost

## From discrete functions to circuits



Jack Kilby  
1958

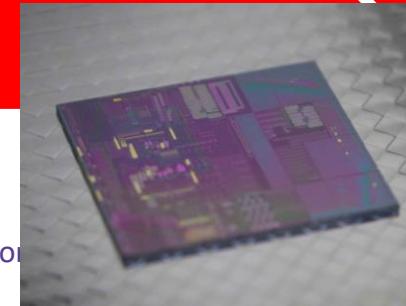
Electronic IC (EIC)



Silicon technology

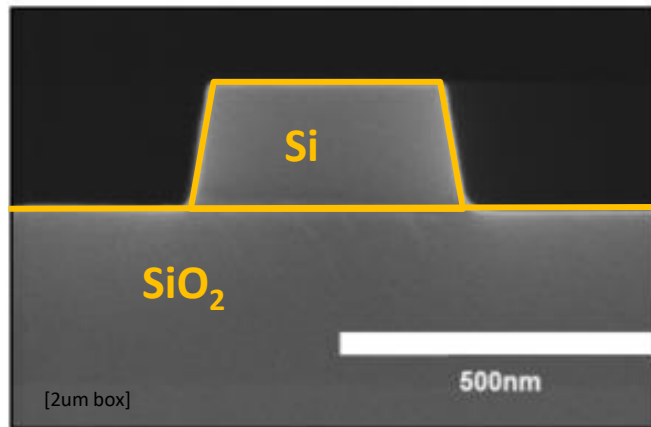
~2000

Photonic IC (PIC)



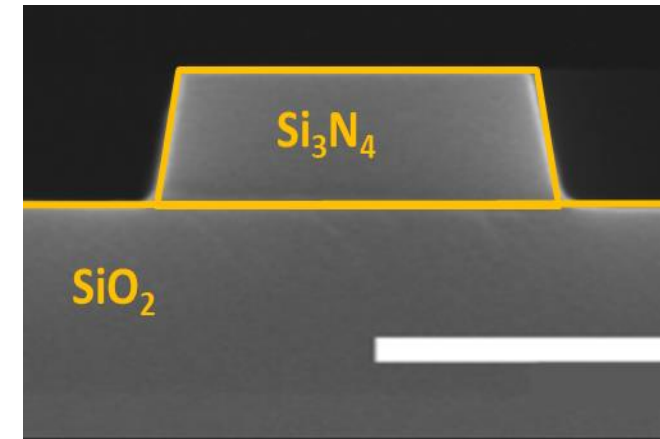
# Silicon photonics: Two CMOS –fab compatible families

## Silicon-on-Insulator (SOI)



Silicon:  $n=3.5$   
Silicon oxide:  $n=1.45$   
Very high index contrast

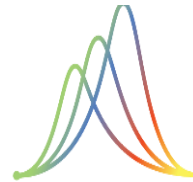
## Silicon nitride (SiN)



Silicon nitride:  $n=2$   
Silicon oxide:  $n=1.45$   
Moderately high index contrast



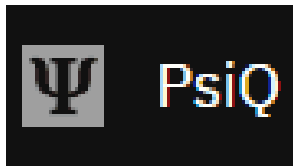
# Main product today: transceivers for datacom and telecom



**Under development:**  
**Data rate: 800 Gb/s**  
**Symbol rate: 100 Gbaud**

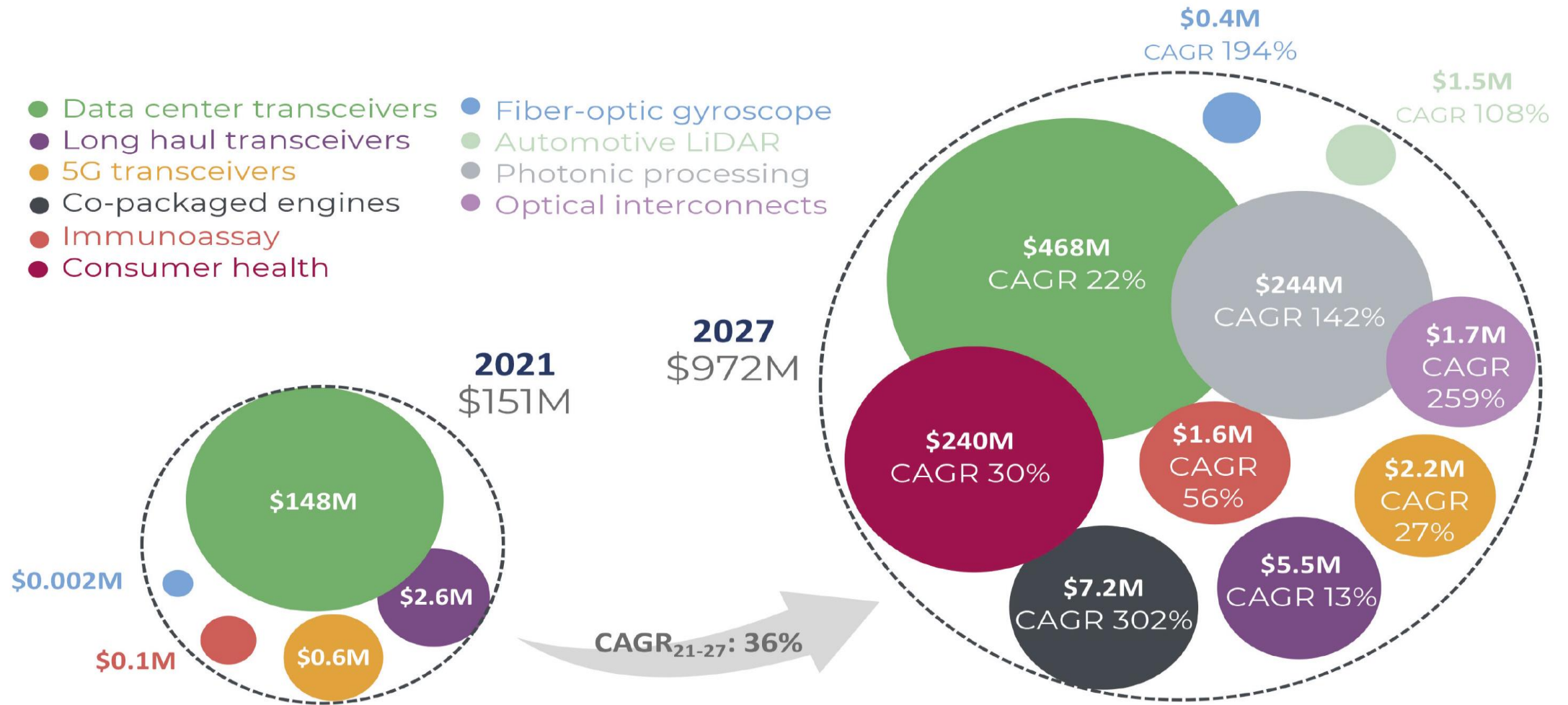


# Silicon photonics going beyond transceivers



# 2021-2027 SILICON PHOTONIC DIE FORECAST BY APPLICATION

Source: Silicon Photonics 2022 Report, Yole Intelligence, 2022

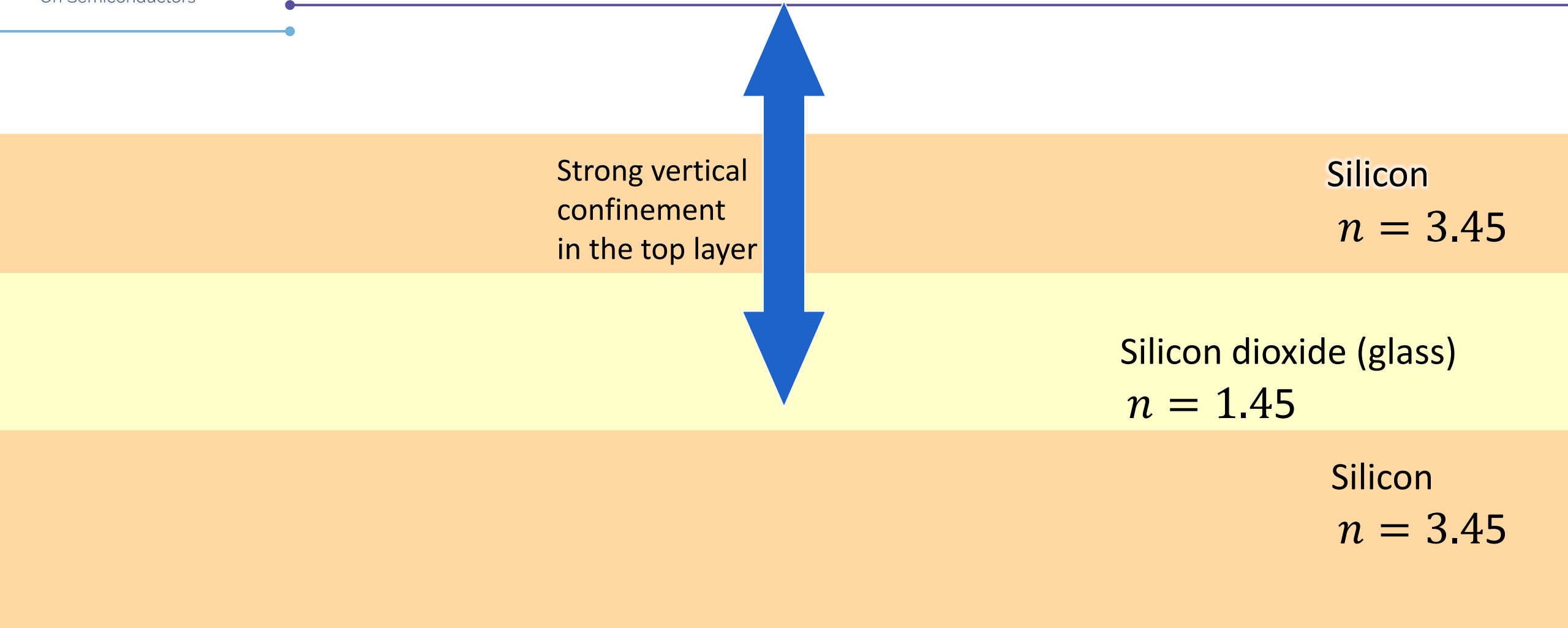


# Current state & future evolution of silicon photonics

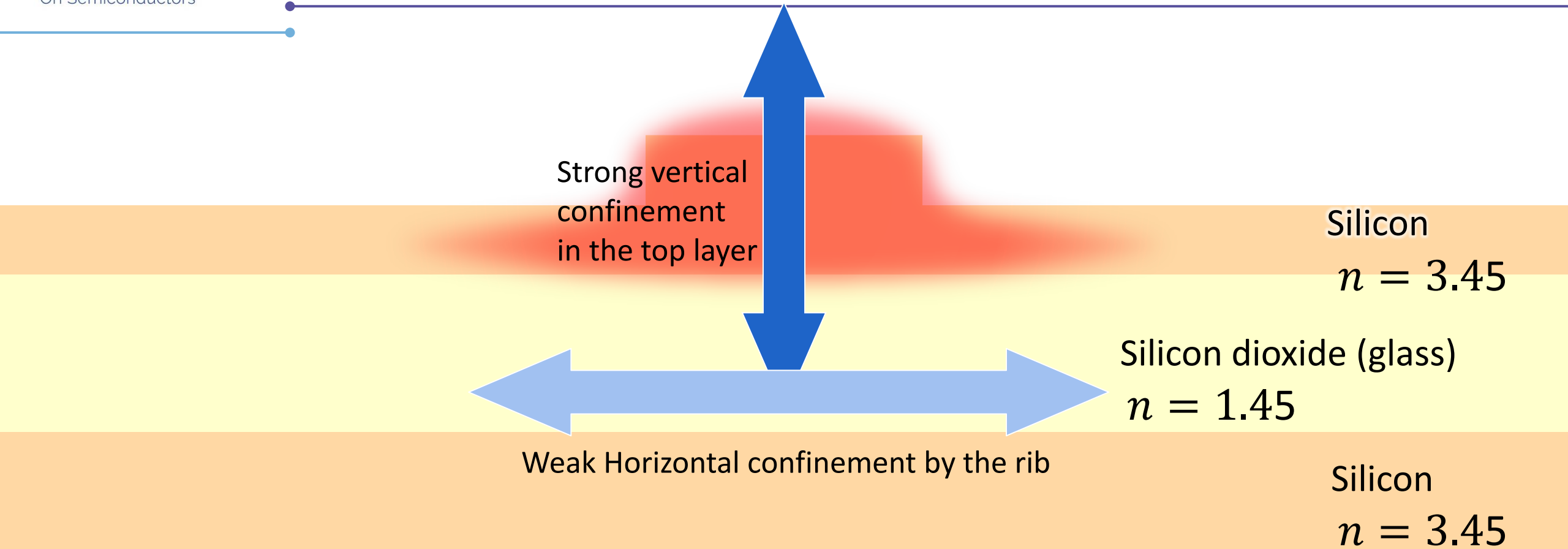
- From technological lens
- From value chain lens + Europe's position



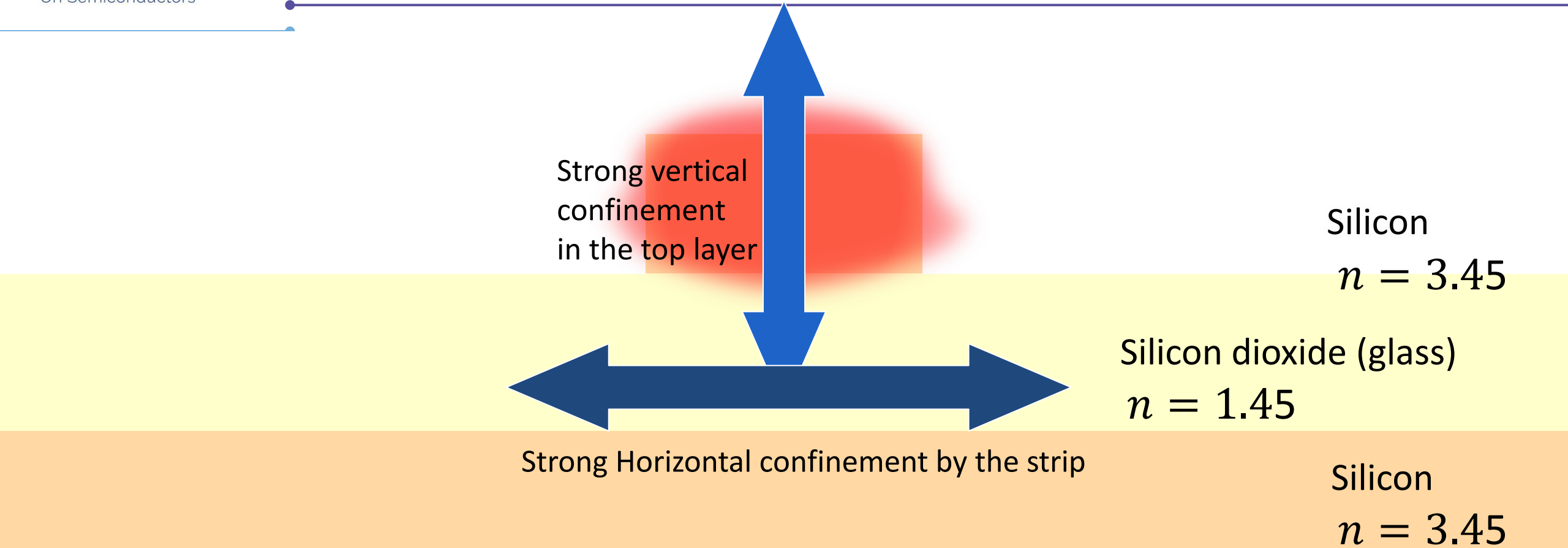
# Silicon photonics waveguide stack

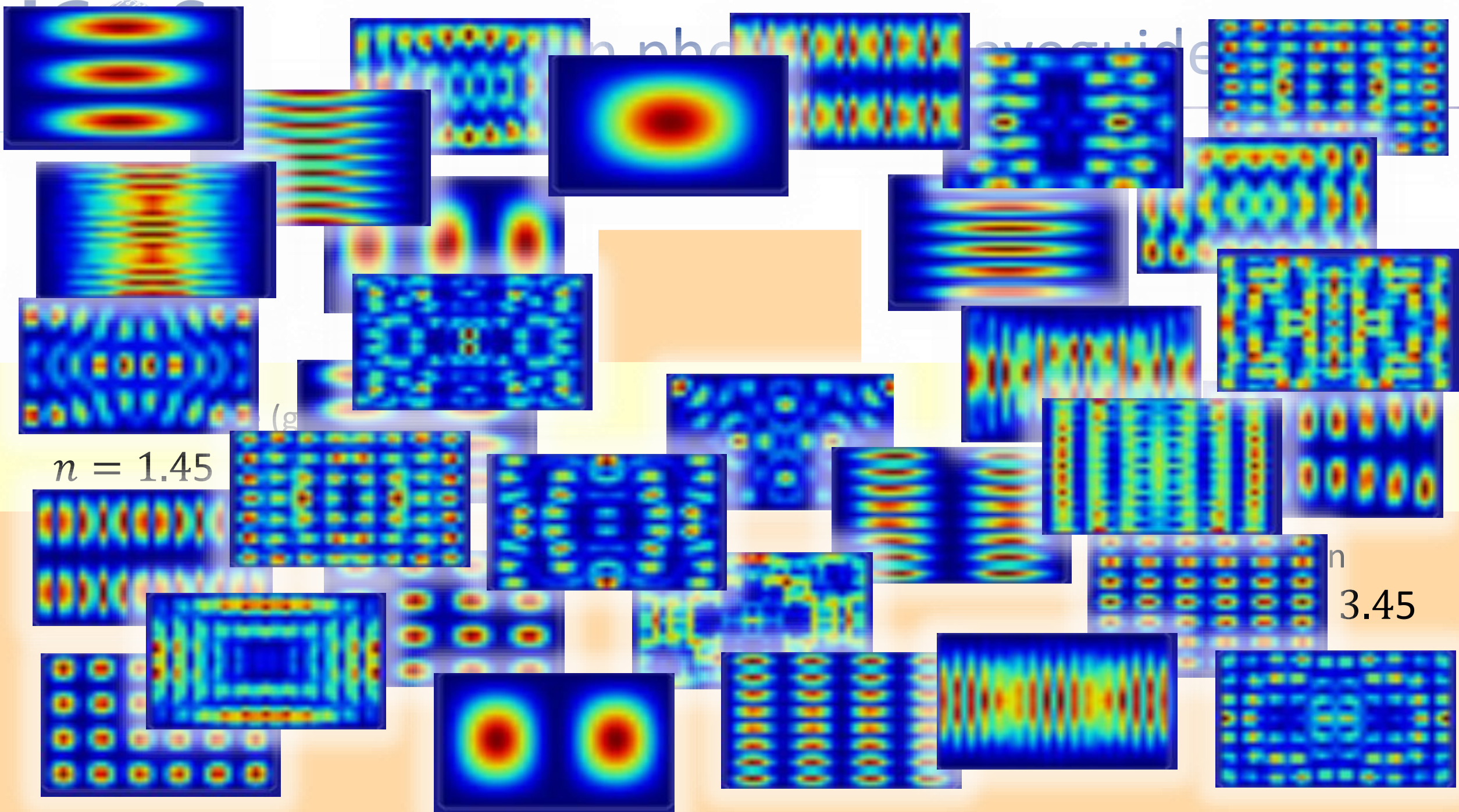


# Silicon photonics rib waveguide



# Silicon photonics strip waveguide





$n = 1.45$

$n = 3.45$



# Shrinking SOI waveguides

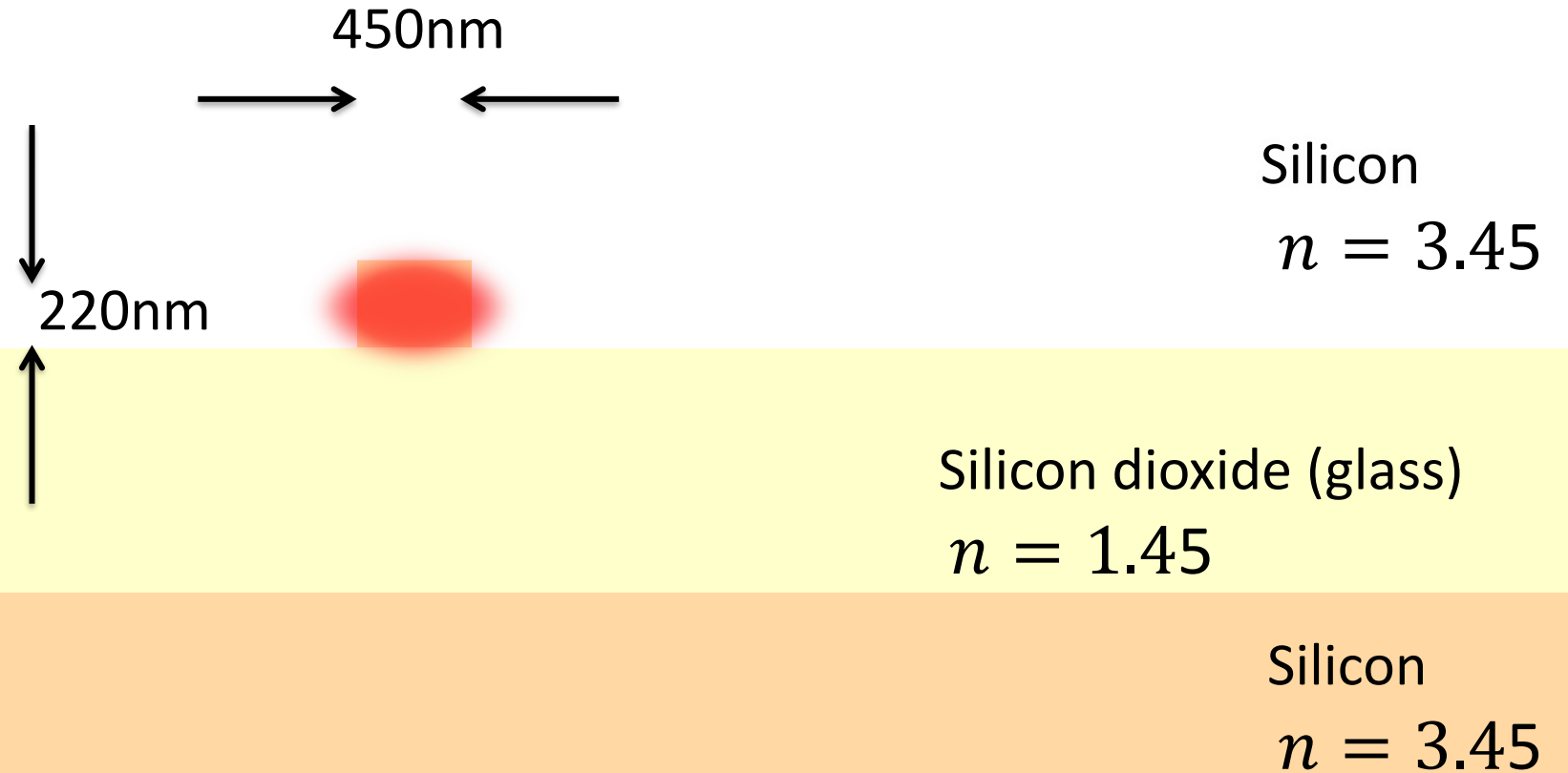


Silicon  
 $n = 3.45$

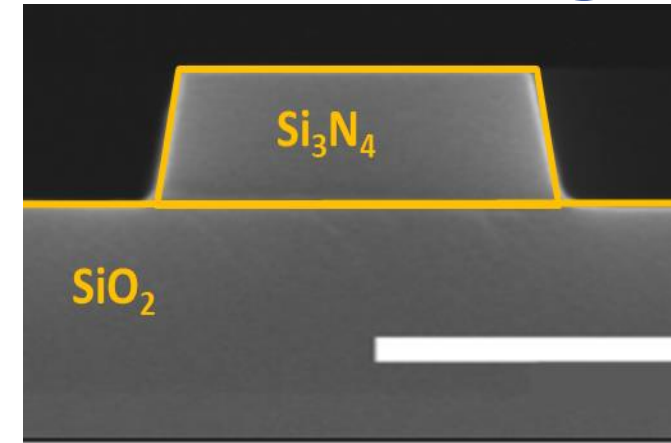
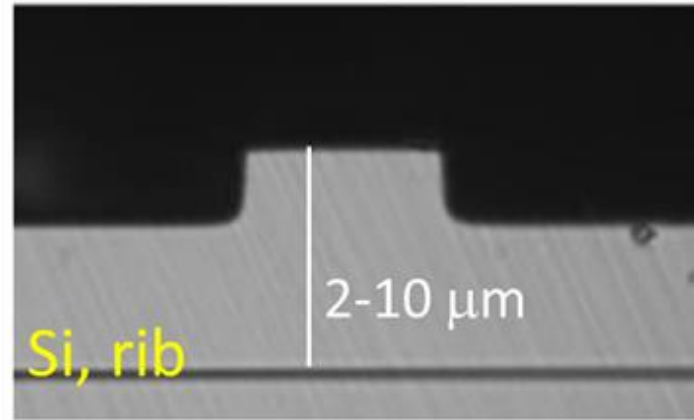
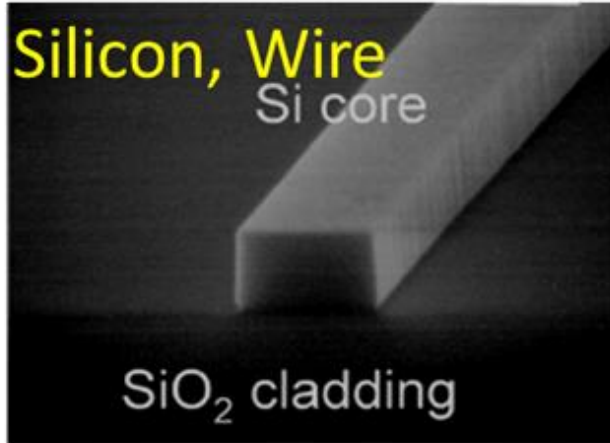
Silicon dioxide (glass)  
 $n = 1.45$

Silicon  
 $n = 3.45$

# Shrinking SOI waveguides



# Current state and future evolution: Waveguides



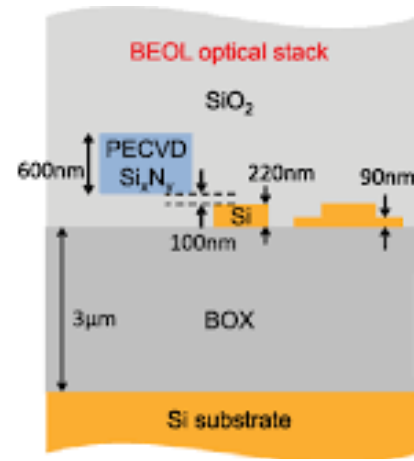
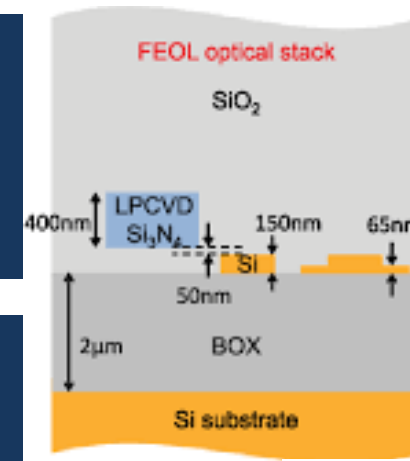
## Performance:

Propagation loss:  $\sim 0.5\text{--}2$  dB/cm

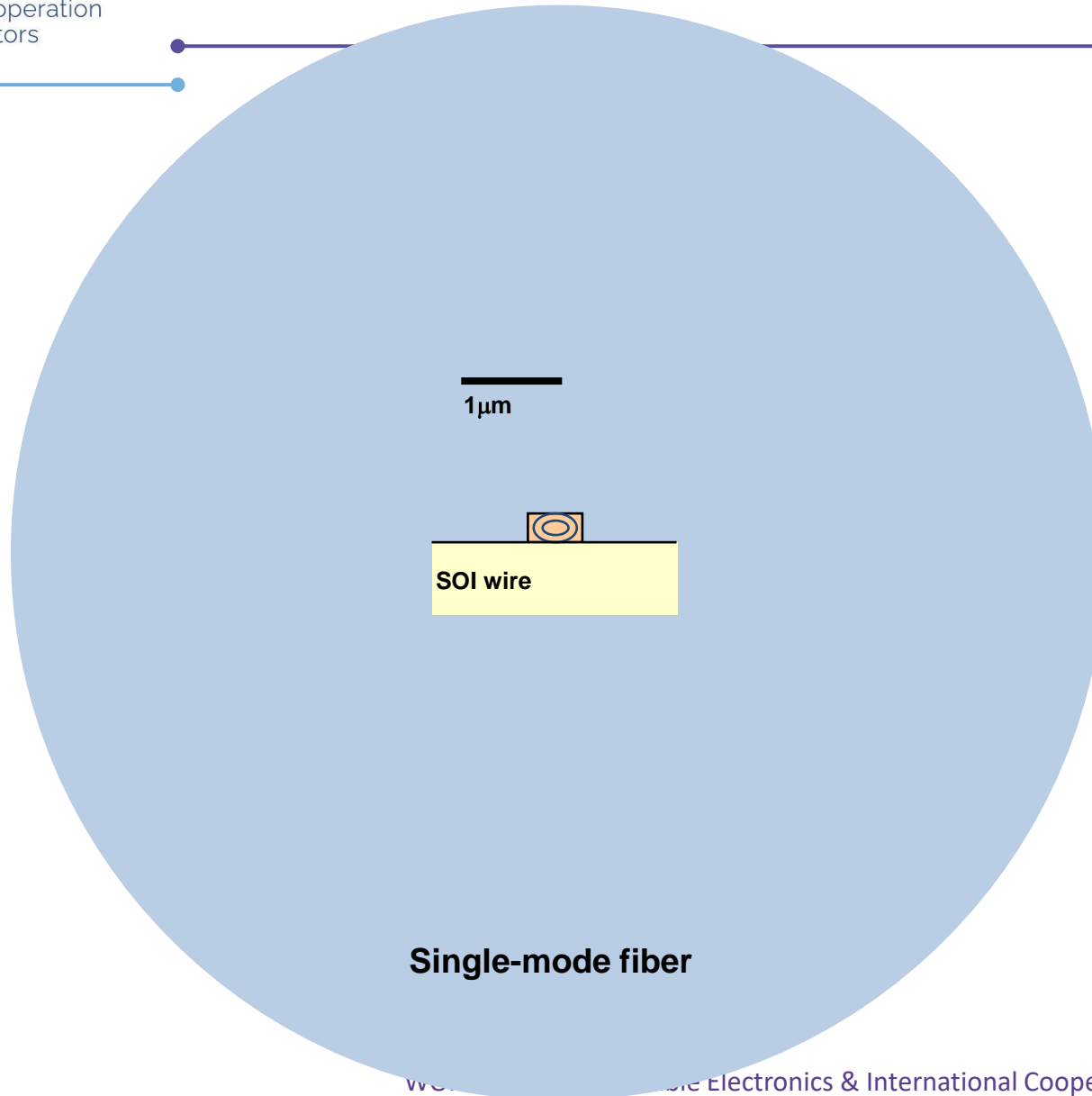
Bending radius: 5 – 20 micron

## Future evolution:

- Better process control (every  $\text{nm}^3$  matters)
- Substrate quality
- Multilayer platforms with medium index contrast guiding layers



Source: J. Poon, JLT

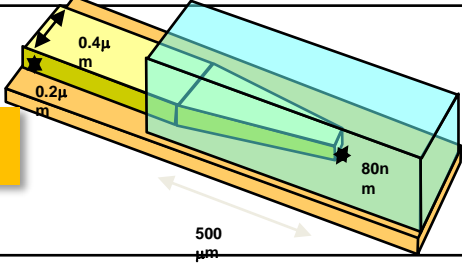
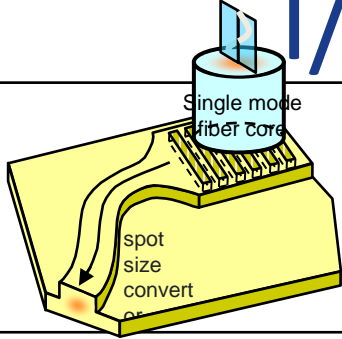


## Requirements

- Low loss
- Broadband
- High coupling tolerance
- No facet reflections
- Wafer-scale testability
- Easy to fabricate

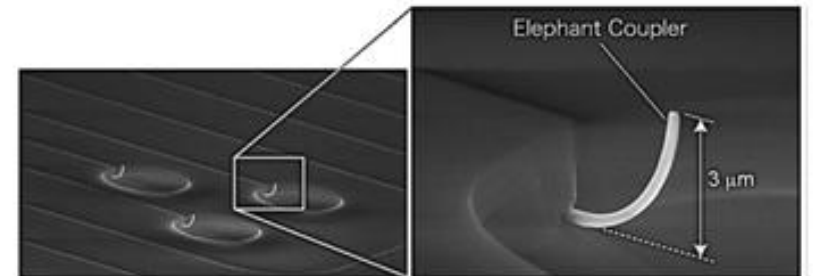


# Current state and future evolution: I/O devices

|                               | <b>Inverted taper</b>  | <b>Grating coupler</b>  |
|-------------------------------|--|---|
|                               |  |  |
| <b>Loss (best)</b>            | <1dB   | <1dB  |
| <b>Loss (in real live)</b>    | 2dB-7dB  | 3dB-7dB   |
| <b>Broadband</b>              | > 100nm  | 35nm (1dB)  |
| <b>Misalignment tolerance</b> | 1um (1dB)  | 2.5um (1dB)   |
| <b>Facet reflections</b>      | Low  | -20dB   |
| <b>Waferscale testing</b>     | No   | Yes   |

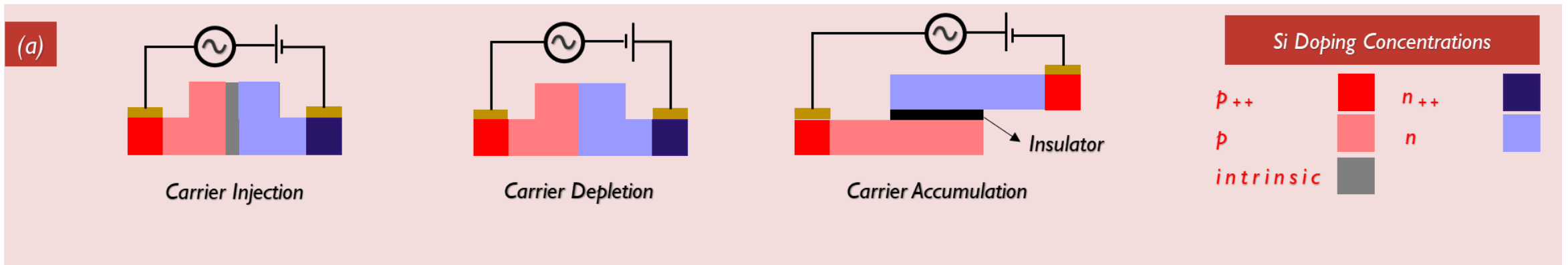
## Future evolution:

- Better process control
- Substrate quality WiW and WtW
- New designs



T.Yoshida, IPR

# Current state and future evolution: High-speed phase modulators



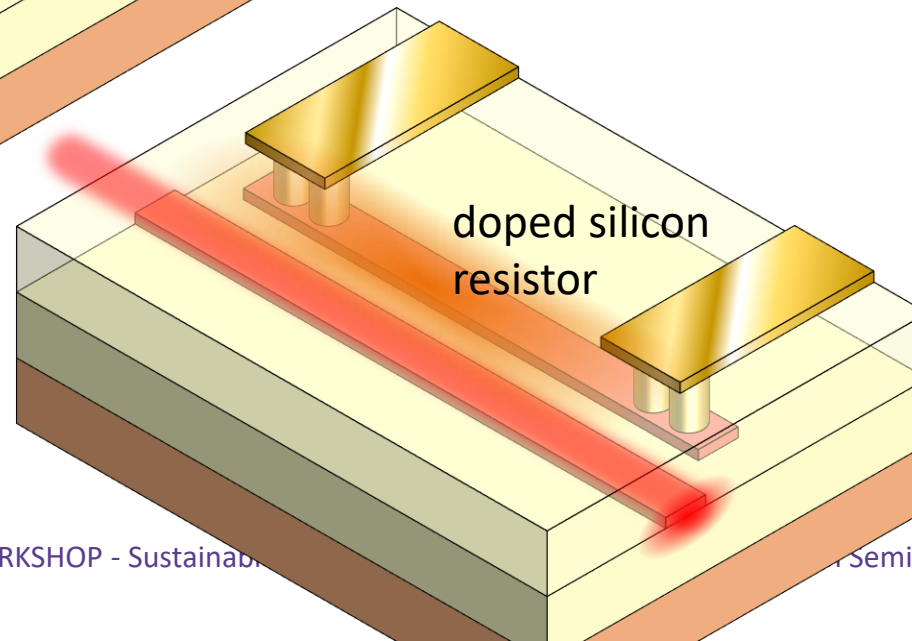
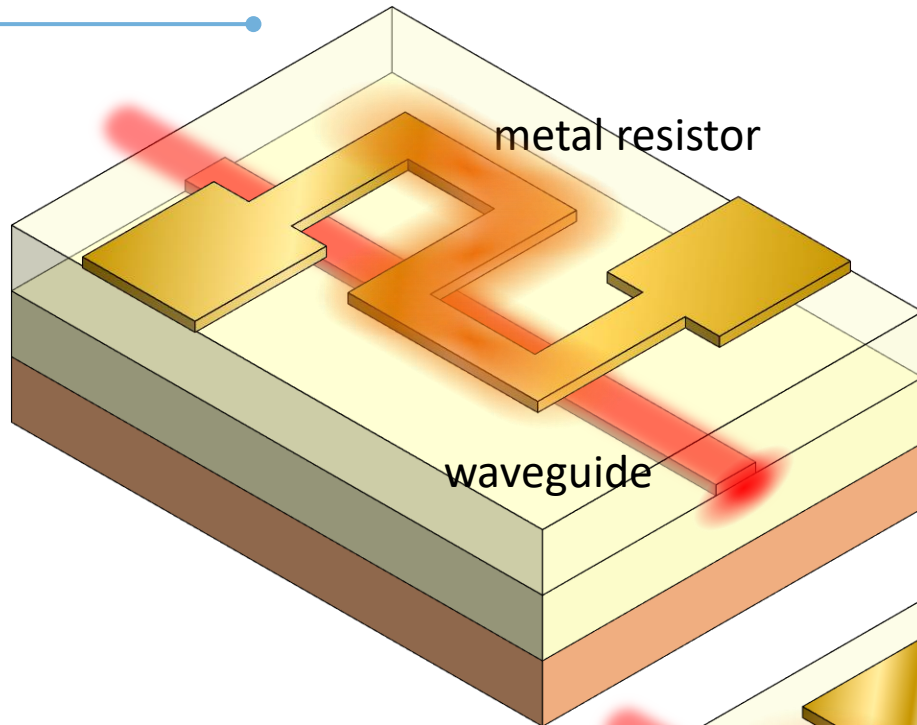
**Table 2** Typical and state-of-the-art performance matrix for the plasma dispersion high-speed phase modulators. The parentheses contain the best-reported result for a performance attribute. The matrix includes the results reported for O-band and C-band demonstrations.

| Principle                         | Modulation efficiency      |                               | Length <sup>a</sup> of phase shifter (mm) | Data rate <sup>b</sup> (Gb/s) | Energy/bit (fJ/bit)   |
|-----------------------------------|----------------------------|-------------------------------|---|-------------------------------|---|
|                                   | $V_{\pi} \cdot L$ (V · cm) | Loss (dB/cm)                  |   |                               |   |
| Carrier injection <sup>c</sup>    | <0.5 (0.058 <sup>8</sup> ) | ~70 (28 <sup>7</sup> )        | ≥0.1 to <0.3                              | <40 (70 <sup>7</sup> )        | ~1000 for MZMs and RMs (0.1 <sup>1,98</sup> )                         |
| Carrier accumulation <sup>d</sup> | <0.3 (0.16 <sup>69</sup> ) | 50 to 80 (~35 <sup>69</sup> ) | ≤0.5                                      | ~40 (40 <sup>5</sup> )        | >200 for MZMs, <200 (3 <sup>105</sup> ) for SLMs <sup>9</sup>         |
| Carrier depletion <sup>e</sup>    | ~2 (0.52 <sup>9</sup> )    | 10 to 30 (2.6 <sup>10</sup> ) | >1  | >40 (100 <sup>122,123</sup> ) | ~200 for MZMs (32.4 <sup>19</sup> ), <40 for RMs (0.9 <sup>18</sup> ) |

## Future evolution:

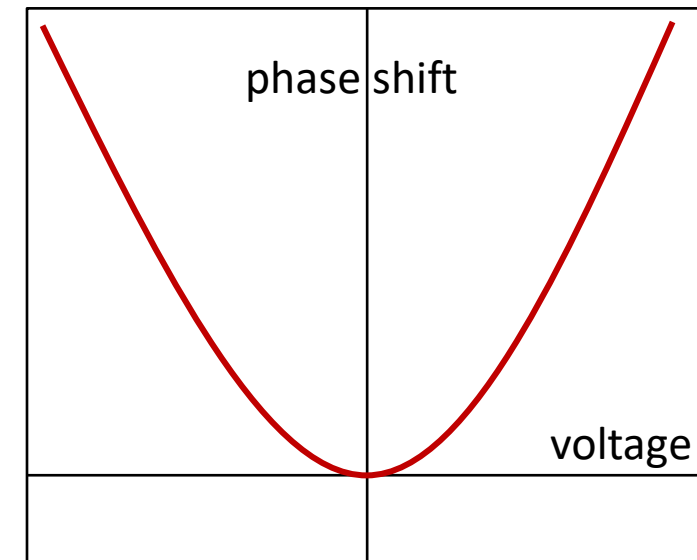
Integration of novel materials (Ferroelectrics, 2D, Polymers, SiGe, III-Vs, etc.) for low  $V_{\pi}$ , low loss, high bandwidth, and low energy pure phase shift

# Low-speed phase shifter by heaters

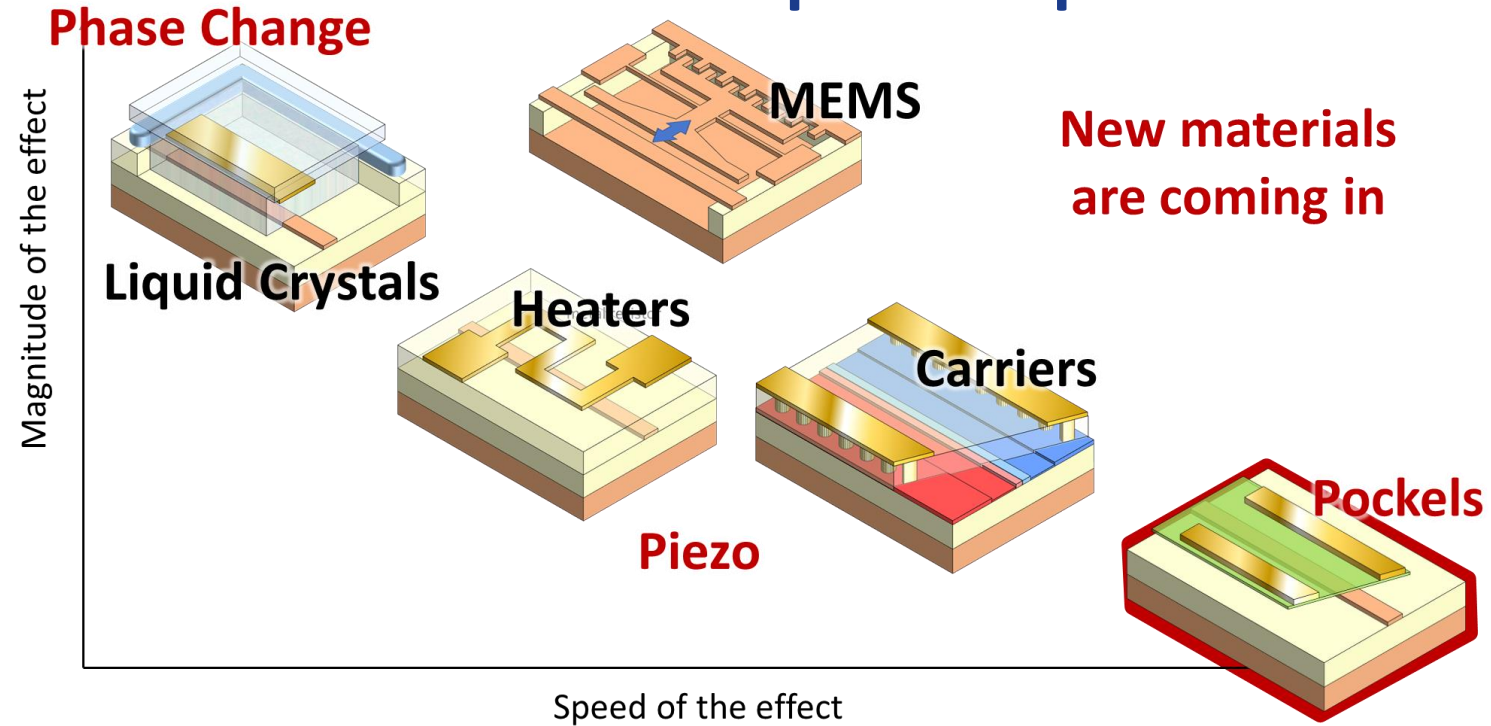


- Waveguides are thermally sensitive:  

$$\Delta\phi \sim \Delta n_{eff} \sim T \sim P_{elec} \sim V^2 \sim I^2$$
- Integrate resistor close to the waveguide
- efficiency:  $P_{\pi} \approx 5 - 30mW$   
 (for silicon waveguides)



# Current state and future evolution: Low-speed phase modulators



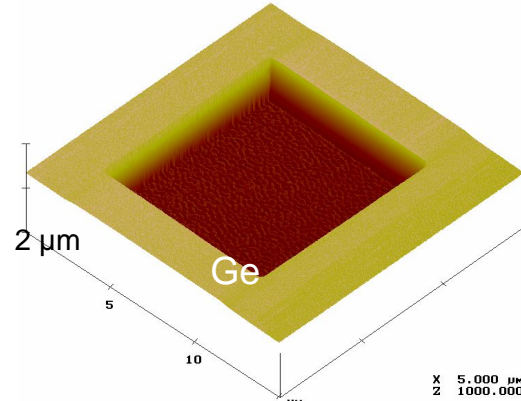
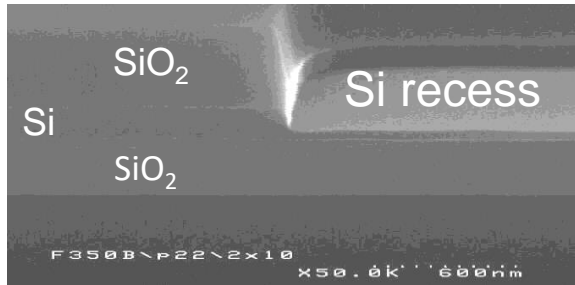
## Future evolution:

Integration of novel materials for more efficient (power, loss, crosstalk) low-speed phase shifters

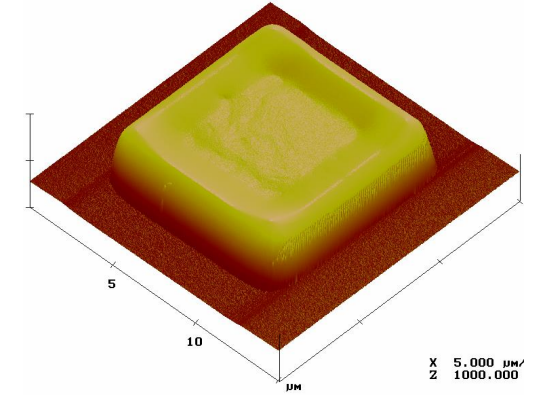
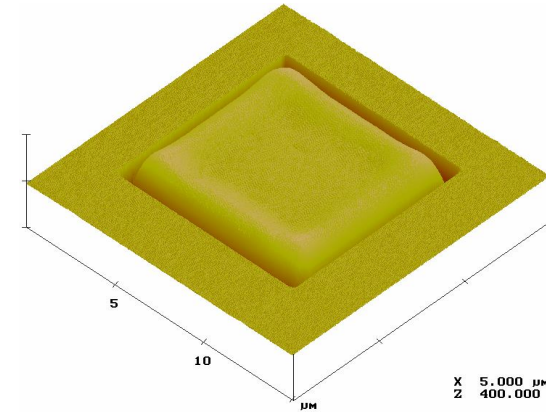


# Current state and future evolution: photodetectors

## Two RPCVD steps to overcome lattice mismatch issue



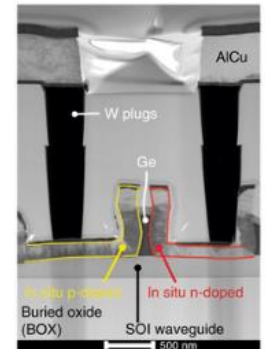
Ge « Seed » layer  
400° C, 60s



| Photodetectors         | [unit]                       |                 |
|------------------------|------------------------------|-----------------|
| Absorption             | $\alpha$ (cm <sup>-1</sup> ) | 10 <sup>3</sup> |
| Dark Current           | I (nA)                       | 0.2             |
| Responsivity (p-i-n)   | R (A/W)                      | 1               |
| Bandwidth (p-i-n)      | B (GHz)                      | >100            |
| Gain x Bandwidth (APD) | GB (GHz)                     | 300             |
| Guided Power*          | mW                           | 30              |

### Future evolution:

- Better process control for narrower intrinsic regions
- Lower defect density for lower dark currents



S. Lischke,  
Nat. Photonics

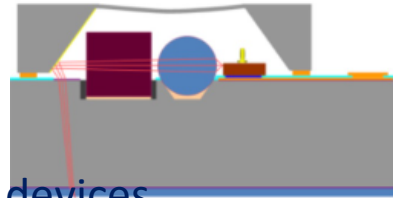


# Current state and future evolution:

## Light sources

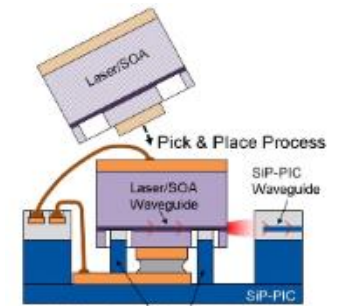
### LaMP

- ✓ Use mature III-V technology
- ✓ Wafer level test on source
- ✓ Known good die
- No waveguide-in / waveguide-out devices
- Sequential population of SiPhwafer



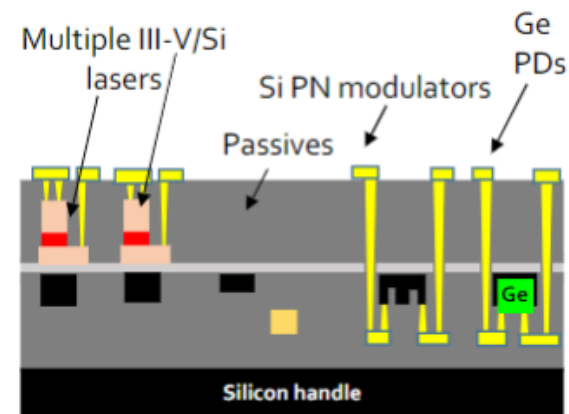
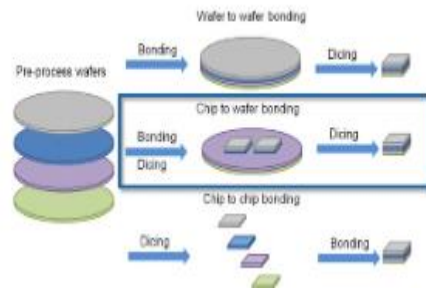
### Flip-chip Integration

- ✓ Use mature III-V technology
- ✓ Wafer-level test on source
- ✓ Known good die
- ✓ Fairly efficient optical coupling
- Sequential population of SiPhwafer
- Requires local back-end removal

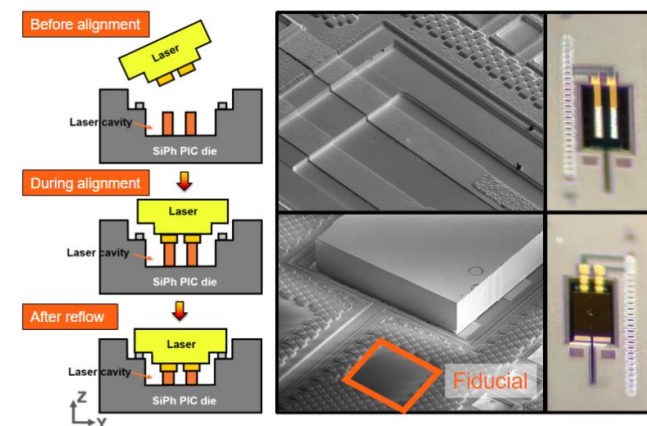


### Die-to-wafer bonding

- ✓ Efficient optical coupling
- ✓ Parallel processing of devices
- ✓ Wafer-level test on target wafer
- III-V processing on target wafer
- No known good III-V die



SCINTIL Photonics

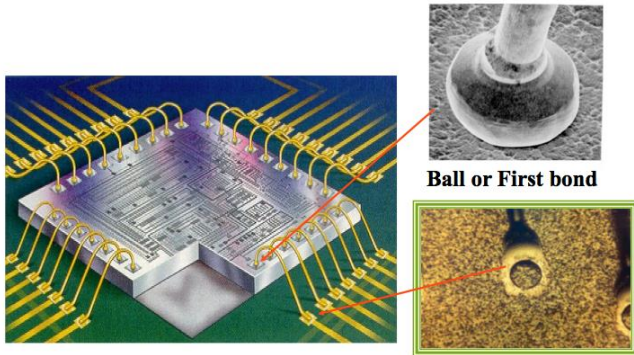
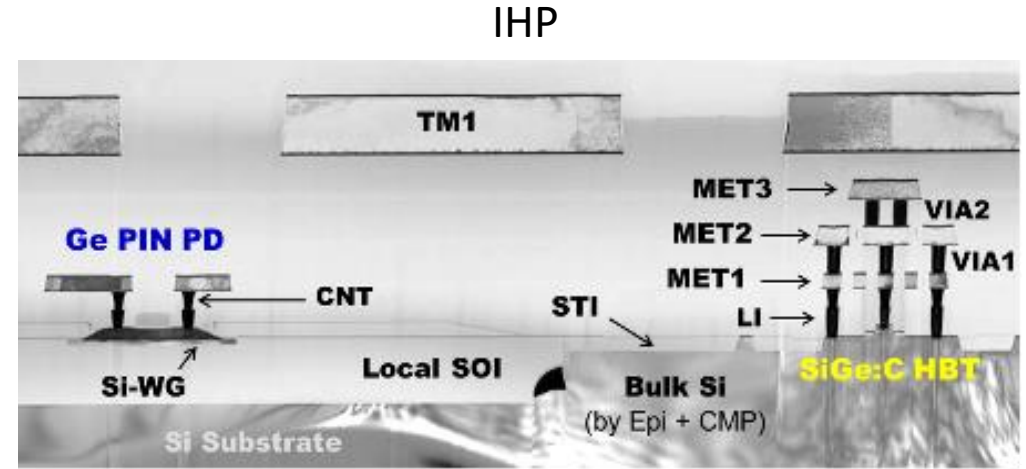


GlobalFoundries

# Current state and future evolution : electronic-photonic integration



STMicro.



Tyndall

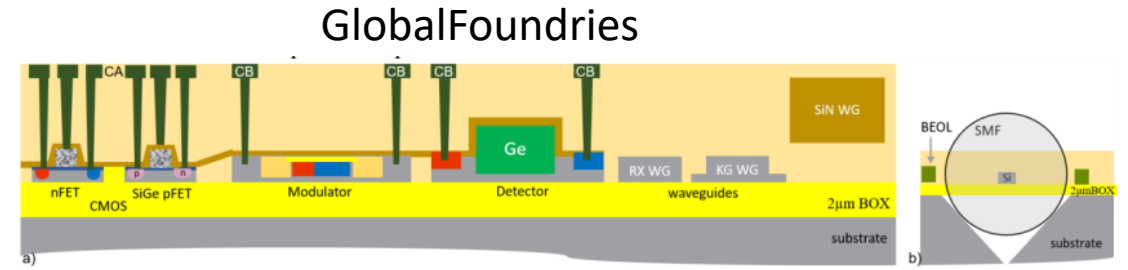


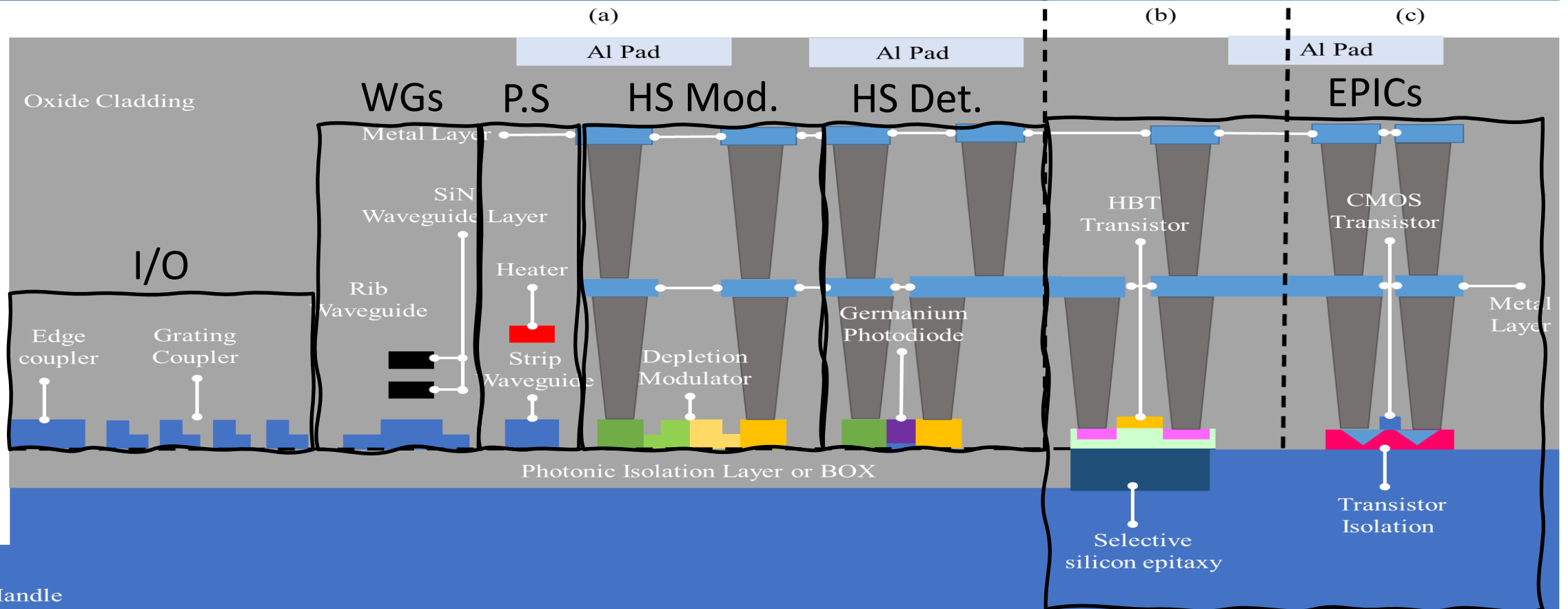
Fig. 1. (a) Cross-section showing front end and middle of line of 45CLO technology. (b) Cross-section diagram of the IOSMF with v-groove and the attached fiber.

**Future Evolution:** Higher intimacy between electronics and photonics becoming more important

# A generic cross-section of a silicon photonics platform

Representative cross-section of a silicon photonics process

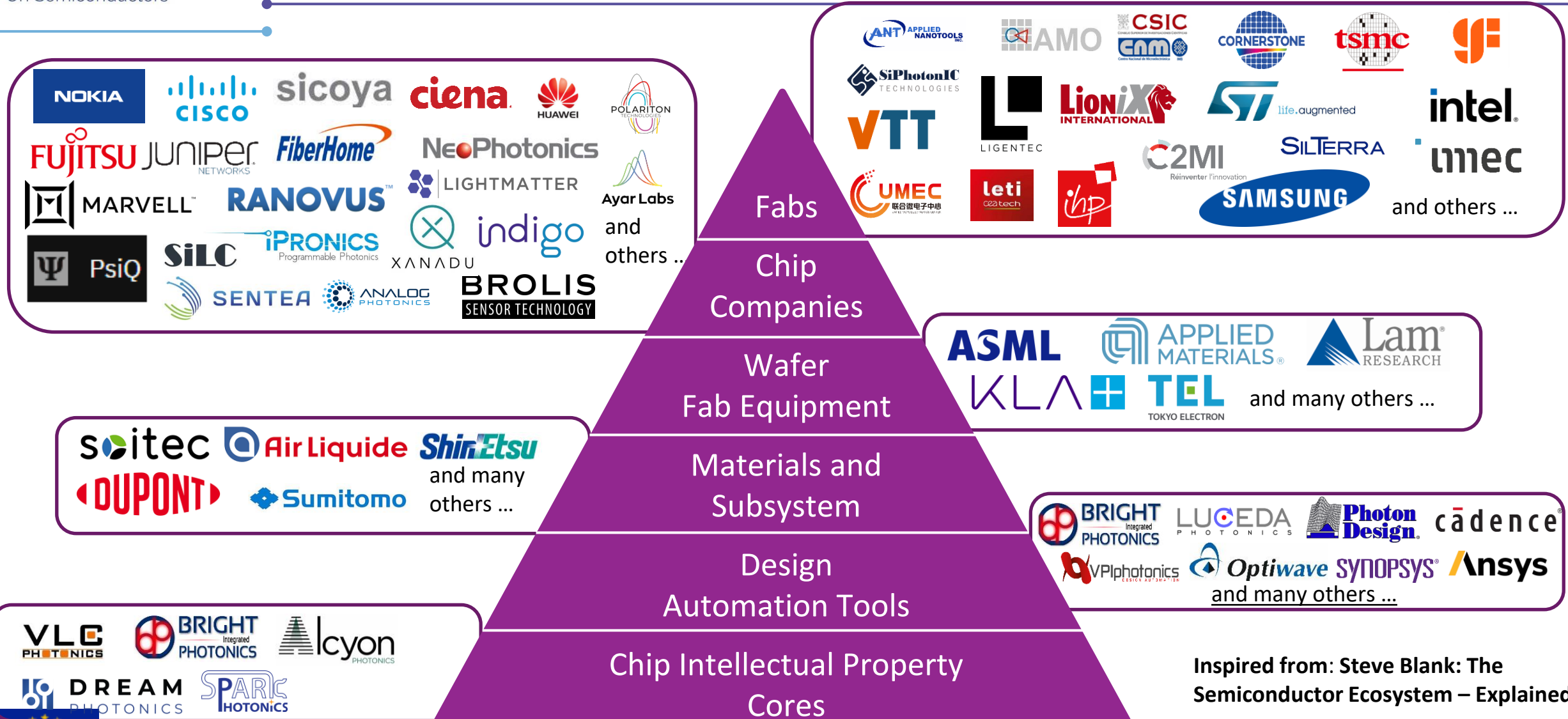
Representative cross-section of a silicon photonic process combining photonics with electronics (b) with BICMOS process (c) with Bulk Si or PD-SOI



# Current state & future evolution of silicon photonics

- From technological lens
- **From value chain lens + Europe's position**

# Silicon photonics value chain



Inspired from: Steve Blank: The Semiconductor Ecosystem – Explained







**EPOSS**  
European Association on  
Smart Systems Integration



# White Paper on Integrated Photonics

authored by a Joint Focus Group of the  
**European Association on Smart Systems Integration (EPOSS)**  
and  
**Photonics21**

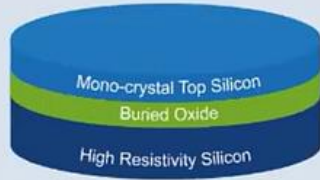
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Michael Scholles, Michael J. Wale, Timo Aalto, Mohand Achouche, Luc Augustin, David Bitauld, Sonia Garcia Blanco, Patrick Coge, Marcus Dahlem, Paul van Dijk, Gerhard Domann, Amir Ghadimi, Martijn Heck, Thomas Hessler, Andreas Klug, Renaud de Langlade, Martin Martens, Christian Meyne, Clifford Murray, Sybille Niemeier, Ruud Oldenbeuving, Mehmet Cengiz Onbaşı, Joseph Pankert, Ryszard Pyramidowicz, Abdul Rahim, Graham Reed, Jelmer Renema, Ewit Roos, Martin Schell, Elisabeth Steinmetz, Martin Strassburg, Bertrand Szelag, Tolga Tekin, Dao Thang Duy, Dries van Thourhout, Marija Trajkovic, Gintaras Valusis, Lennart de Vreede, Markus Wilkens, Martina Wisniewski, Benjamin Wohlfeil, Lars Zimmermann

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April 2023

# Ecosystem status: materials and substrates



**200-mm  
Photonics-SOI**

- Sub- $\mu\text{m}$  Si waveguides
- >120-nm SiPho process CDs
- Lower process cost
- Ideal for cost-sensitive applications



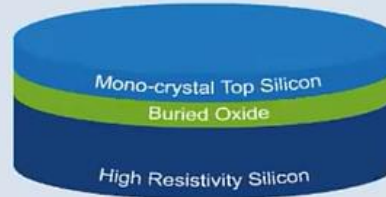
Transceivers

NPO Optical Engine



3D Sensing

Short-range LiDAR



**300-mm  
Photonics-SOI**

- Sub- $\mu\text{m}$  Si waveguides
- Advanced SiPho process nodes (down to 40nm)
- Advanced packaging
- Ideal for cutting-edge applications



Transceivers

CPO Optical Engine



Automotive LiDAR

Machine Vision



Quantum

Optical Computing



**200-mm  
Photonics-SOI + EPI**

- Multi- $\mu\text{m}$  Si waveguides
- Legacy SiPho process nodes (>200nm)
- Low dispersion / High-power handling
- Ideal for hyperspectral sensing



Healthcare Sensing

High-power LiDAR

## Europe's position

- ✓ One of the largest SOI wafer manufacturer is based in Europe (SOITEC)
- ✓ Close collaboration of EU fabs and substrate manufactures to meet future substrate demands (wafer sizes, uniformity)
  - Diversity of material systems makes it difficult for substrate manufactures to make a bet (a lot of parallel R&D)
  - Access to novel material likes TFLN and EUs push to include novel materials with SiPh.

# Ecosystem status: electronic photonic design automation

- Large EDA vendors (that are mostly US-centric organizations) offer integrated photonics design frameworks
- The fab PDKs are getting rich but still lack compact models and not at-par with electronic PDKs
- Lack of unified process flow for electronic-photonics co-design
- Lack of standardization and no incentive in doing that
- Limited number of design houses and IP vendors





# Ecosystem status: electronic photonic design automation

## Europe's position

- ✓ A number of smaller but collaborative companies offering best-in-class for various aspects of photonic design flow
- ✓ Close relationship of the stakeholders with EU and non-EU foundries to support various PIC platforms
  - Challenges in attracting and retaining talented HR, limited scale-up funding, limited business in EU
  - Asia and US driving the narrative and winning the business



# Ecosystem status: manufacturing

## NORTH AMERICA

**1. ULL Technologies (USA)**

2. Applied Nanotools Inc. (Canada)

3. Intel (USA)

**4. Tower Semicon. (USA)**

**5. Globalfoundries (USA)**

**6. AIM Photonics (USA)**

7. Skorprios Technologies (USA)

8. Skywater (USA)

**9. C2MI (Canada)**

## EUROPE

10. VTT (Finland)

11. SiPhotonic (Denmark)

**12. Imec (Belgium)**

**13. Cornerstone (UK)**

14. IHP (Germany)

**15. LIGENTEC (Swiss.)**

**16. LETI (France)**

**17. CNM-IMB (Spain)**

**18. LioniX Int. (Netherlands)**

**19. STMicro. (France)**

**20. AMO GmbH (Germany)**

**21. CNIT (Italy)**

**22. X-FAB (Germany/France)**

## ASIA

**23. CUMEC (China)**

**24. AMF (Singapore)**

**25. CompoundTek (Singapore)**

**26. SilTerra (Malaysia)**

27. PETRA (Japan)

28. IMECAS (China)

29. SAMSUNG (Korea)

30. Australian Silicon Ph. (Australia)

31. TSMC (Taiwan)

- ★ IDM
- ☆ Pure-play Foundry
- 📍 R&D + Small volume

**View Interactive map:**

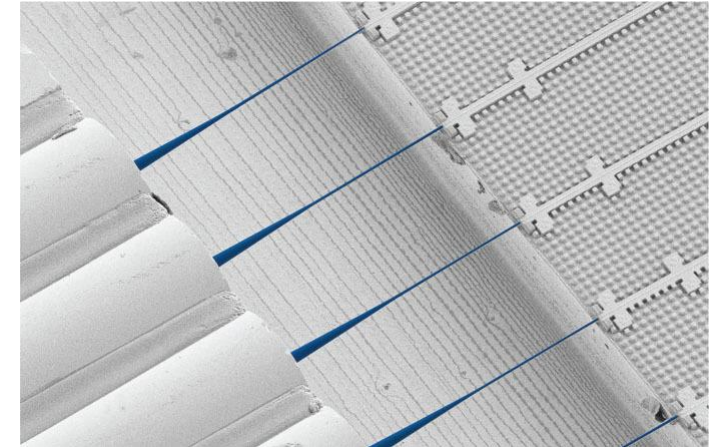
[https://www.google.com/maps/d/edit?mid=1zHWNDRO0OI0M\\_bh6eGerY7ddVOjl8ohE&usp=sharing](https://www.google.com/maps/d/edit?mid=1zHWNDRO0OI0M_bh6eGerY7ddVOjl8ohE&usp=sharing)



## Europe's position

- ✓ Renowned R&D institutes with a an established track record in integrated photonics offering open-access pilot-scale manufacturing of silicon photonics
- ✓ Rich portfolio of platforms with their complementary strengths
- ✓ Full value chain in EU: electronics, photonics, packaging
- No pure-play high-volume and high-end silicon photonics fab today

- 70% of the costs associated with silicon photonic device production arise during this packaging process
- Rapid evolution of technologies and solutions
- Toolmakers have emerged
- Less investment and lack of standardization



Photonics Spectra



Ficontec PIC Assembly Tool



## Europe's position

- ✓ Know-how, expertise both a pilot-scale and beyond
- ✓ EU equipment providers for assembly and packaging
  - Lack of co-design tools and lack of experts
  - Dominance of outsourcing to Asian suppliers

**ficonteC**  
photonics assembly & testing

**PIXAPP**  
Photonic Packaging  
Pilot Line

**phix**



**Fraunhofer**  
IZM

**AIXEMTEC**

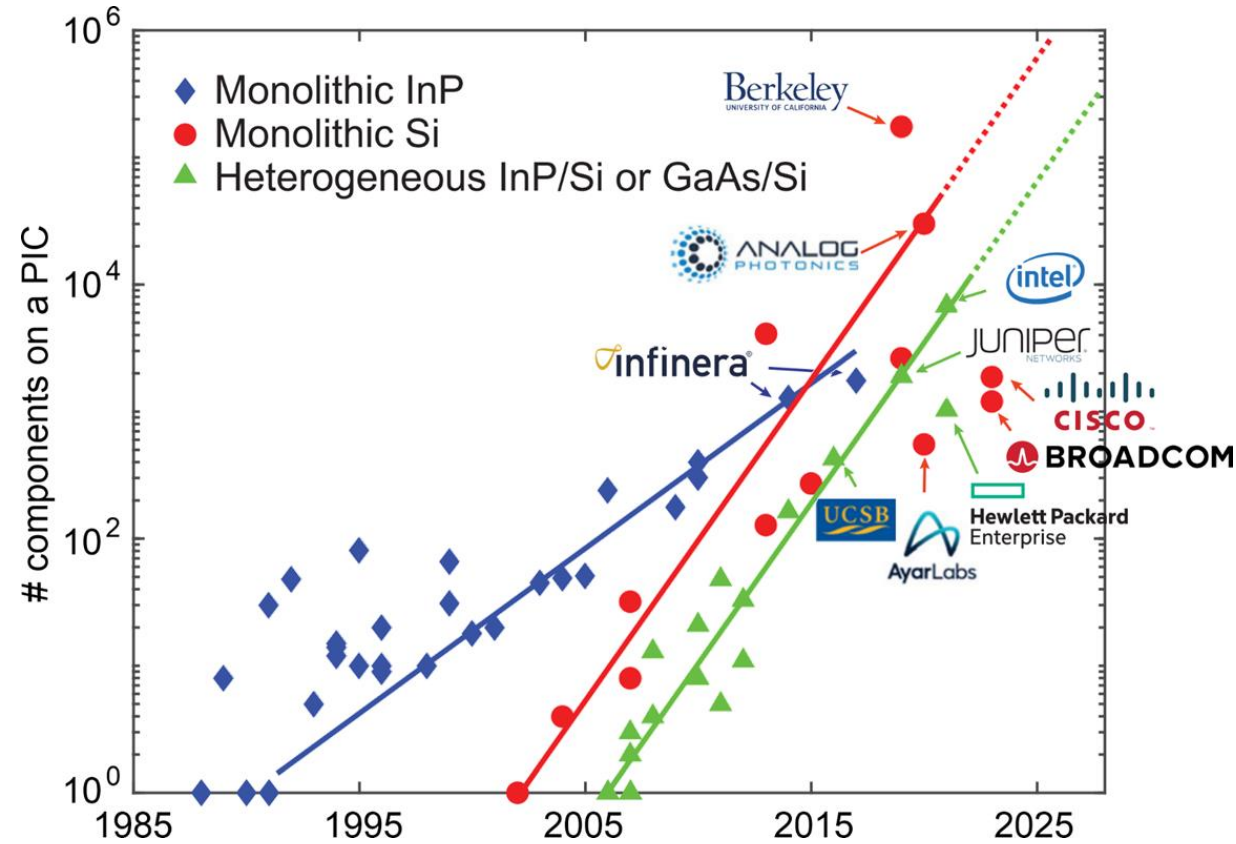
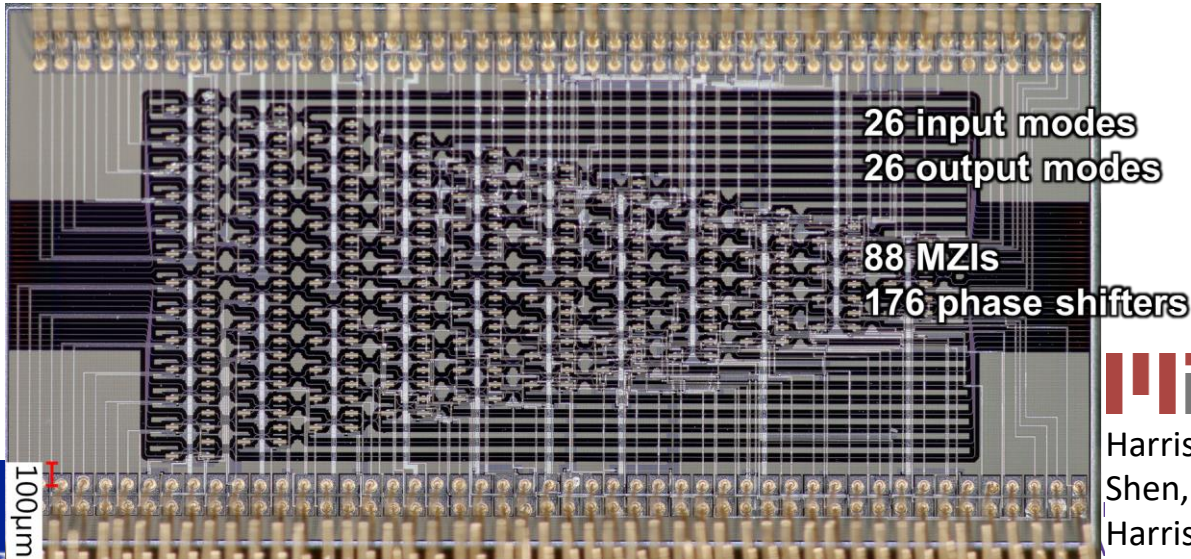
**vanguard**  
PHOTONICS  
bright connections

# Future trends in silicon photonics



# Future Trends - Large-scale photonic integration

- Growing order of integration; 10Ks of components
- photonics + electronic drivers
- different applications (AI, ML, LiDARs, Computing)
- Small chip volumes (compared to electronics)



Margalit et al, APL, 2021

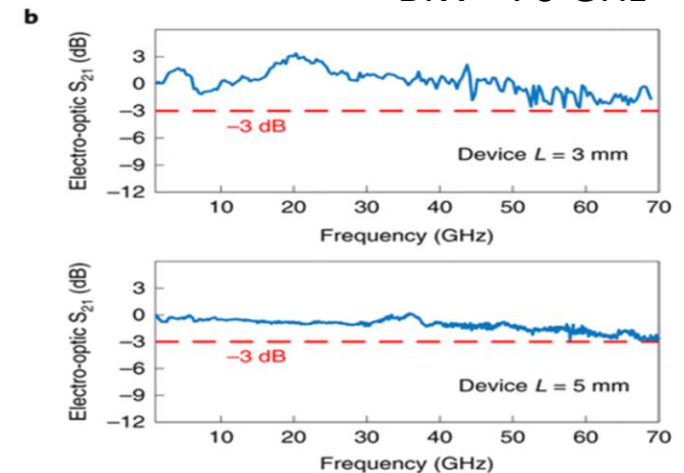
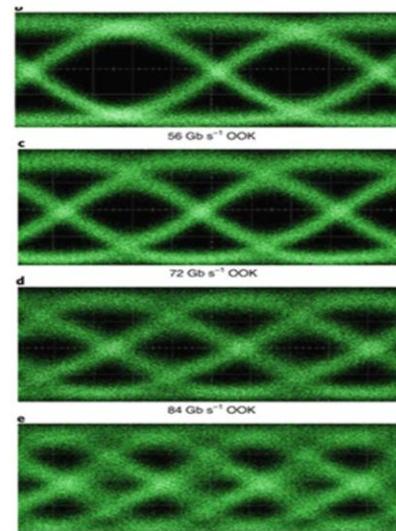
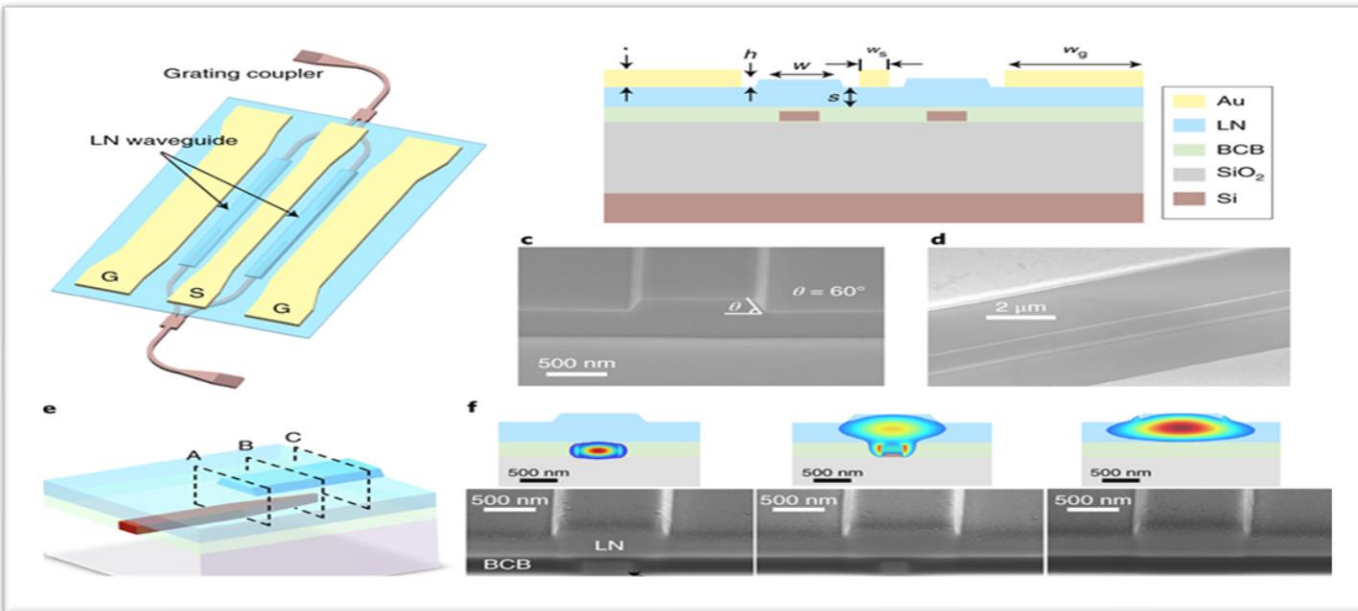


Harris et al, Nature Photonics 2017  
 Shen, Harris et al, Nature Photonics 2017  
 Harris et al, Optica 2018

# Future Trends - Heterogenous silicon photonics

- Wafer-scale integration of novel materials to boost the performance of silicon photonics building blocks
  - Example: high-speed phase modulator

I.L = 2.5 dB  
V<sub>π</sub>.L = 2.2 V.c  
B.W = 70 GHz



<https://www.nature.com/articles/s41566-019-0378-6>

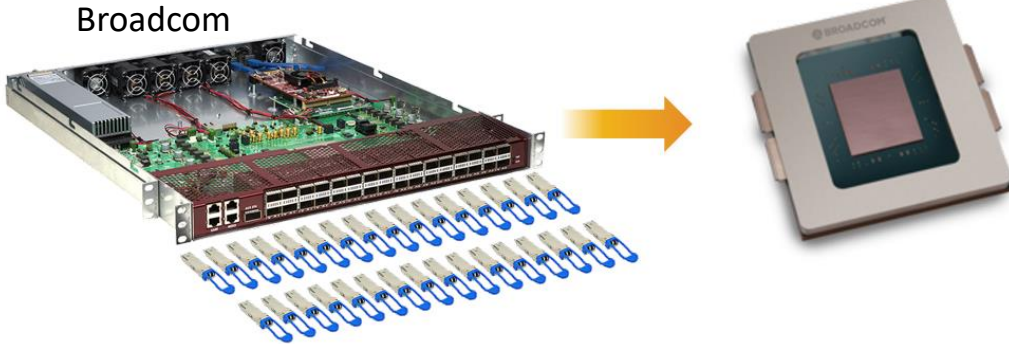


# Future Trends - Enhanced intimacy b/w electronics and photonics

## Co-Packaged Optics

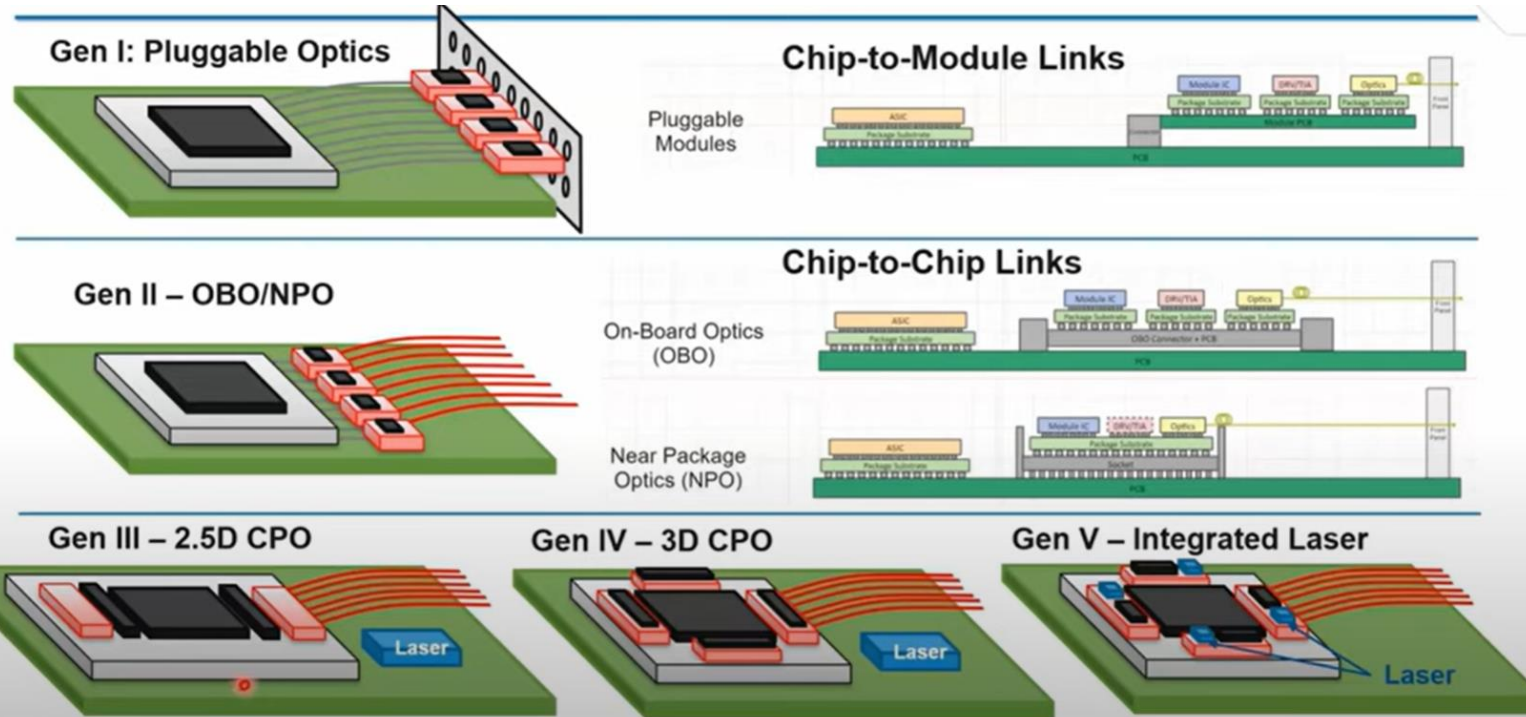
- Integration of optical engines on a common package substrate
- Objective: alleviate the “interconnect density bottleneck”

- Low power
- Low cost
- Low latency
- Higher IO bandwidth



### Challenges:

- Power heat management in ASIC
- Complex assembly
- Difficult field service
- Restricts competition with concentrated R&D to a few companies



# Future Trends - Light source integration

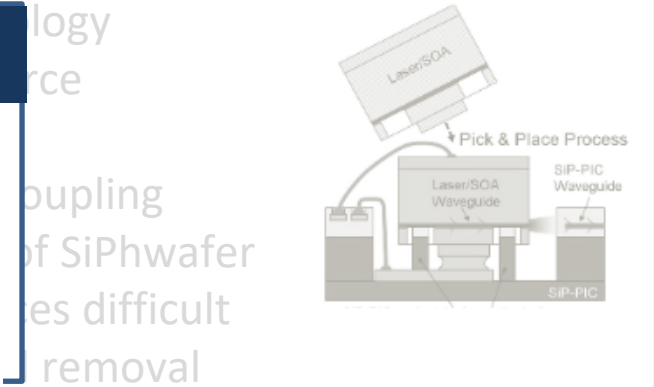
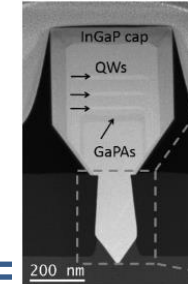
## LaMP

- ✓ Use mature III-V technology
- ✓ Wafer level test on source
- ✓ Known good die
- Fairly efficient optical coupling
- No waveguide-in / waveguide-out
- Sequential population of source
- Can be integrated on back-end

## Flip-chip Integration

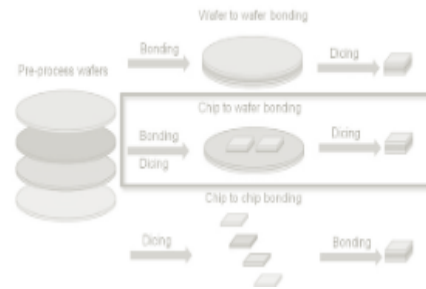
### III-V integration using hetero-epitaxy

- ✓ Front end monolithic integration
- ✓ Efficient evanescent coupling
- Develop completely new process flow
- Demonstrate yield and reliability



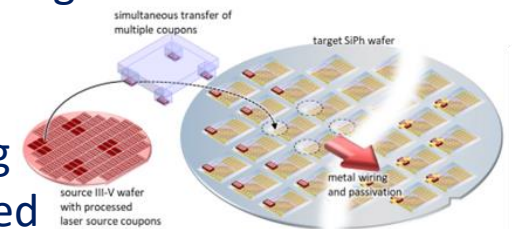
## Die-to-wafer bonding

- ✓ Efficient optical coupling
- ✓ Waveguide in-out devices
- ✓ Parallel processing of devices
- ✓ Wafer-level test on target wafer
- III-V processing on target wafer
- No known good III-V die
- Front-end / back-end NRE



## Micro-transfer printing

- ✓ III-V process & test prior to integration
- ✓ Back-end integration
- ✓ High throughput integration
- ✓ Efficient evanescent coupling
- Supply chain being established
- To demonstrate yield and reliability



- There is a diversity of platforms available in silicon photonics
- Heterogeneous integration provide routes to boost the performance of silicon PIC building blocks
- Datacom/telecom is the major driver today. Other applications are on the horizon
- European silicon photonics eco-system is in a decent shape but has limited design houses, and also lacks an open-access high-volume commercial foundry service.



THANK YOU



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**WORKSHOP - Sustainable Electronics & International Cooperation On Semiconductors**

**[www.icos-semiconductors.eu](http://www.icos-semiconductors.eu)**